

SEARCH REQUEST FORM**Scientific and Technical Information Center**

Requester's Full Name: Amanda Walka Examiner #: 15463 Date: 6/30/2004
 Art Unit: 1752 Phone Number 30 272-1331 Serial Number: 10722815
 Mail Box and Bldg/Rm Location: REH 9D641 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Bib Spec. Attached

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please search for a comp'd of formula I.

Also for Formula I in combination w/ Formula D. Thank you

STAFF USE ONLY		Type of Search	Vendors and cost where applicable
Searcher:	_____	NA Sequence (#)	STN _____
Searcher Phone #:	_____	AA Sequence (#)	Dialog _____
Searcher Location:	_____	Structure (#)	Questel/Orbit _____
Date Searcher Picked Up:	_____	Bibliographic	Dr.Link _____
Date Completed:	_____	Litigation	Lexis/Nexis _____
Searcher Prep & Review Time:	_____	Fulltext	Sequence Systems _____
Clerical Prep Time:	_____	Patent Family	WWW/Internet _____
Online Time:	_____	Other	Other (specify) _____



STIC Search Report

EIC 1700

STIC Database Tracking Number: 126327

TO: Amanda Walke
Location: REM 9D64
Art Unit : 1752
July 12, 2004

Case Serial Number: 10/720815

From: Barba Koroma
Location: EIC 1700
REM EO4 A30
Phone: 571 272 2546

barba.koroma@uspto.gov

Search Notes

Examiner Walke,
Please find attached results of the search you requested. Structures and compounds described were searched in REGISTRY and CAPLUS databases. The results were crossed with appropriate terms.

For your convenience, titles of hits are listed to help you peruse them quickly, followed by a detailed printout of records.

Please let me know if you have any questions.
Thanks.



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact **the EIC searcher or contact:**

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- *I am an examiner in Workgroup:* Example: 1713
- *Relevant prior art found, search results used as follows:*
- 102 rejection
 - 103 rejection
 - Cited as being of interest.
 - Helped examiner better understand the invention.
 - Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- Foreign Patent(s)
- Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ *Relevant prior art not found:*

- Results verified the lack of relevant prior art (helped determine patentability).
- Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28



Page 1Walke10722815

=> file reg
FILE 'REGISTRY' ENTERED AT 16:41:19 ON 12 JUL 2004
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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 11 JUL 2004 HIGHEST RN 708207-86-7
DICTIONARY FILE UPDATES: 11 JUL 2004 HIGHEST RN 708207-86-7

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2004

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> file caplus
FILE 'CAPLUS' ENTERED AT 16:41:22 ON 12 JUL 2004
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FILE COVERS 1907 - 12 Jul 2004 VOL 141 ISS 3
FILE LAST UPDATED: 11 Jul 2004 (20040711/ED)

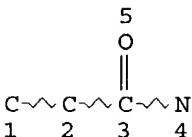
This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d que
L1 1 SEA FILE=REGISTRY ABB=ON PLU=ON POLYVINYL PYRROLIDONE/CN
L6 1 SEA FILE=REGISTRY ABB=ON PLU=ON "POLY(N,N-DIMETHYLACRYLAMIDE)
"/CN

L8 8 SEA FILE=REGISTRY ABB=ON PLU=ON ("SULFONIC ACID LS"/CN OR "SULFONIC ACID, ((3,5-BIS(1,1-DIMETHYLETHYL)-4-HYDROXYPHENYL)METHYL)-, MONOBUTYL ESTER, NICKEL COMPLEX"/CN OR "SULFONIC ACID, PHOSPHINO-"/CN OR "SULFONIC ACIDS"/CN OR "SULFONIC ACIDS, ALKANE, CHLORO"/CN OR "SULFONIC ACIDS, ALKANE, CHLORO, SODIUM SALTS"/CN OR "SULFONIC ACIDS, ALKANE, SODIUM SALTS"/CN OR "SULFONIC ACIDS, ALKANEDI-, DISODIUM SALTS"/CN OR "SULFONIC ACIDS, ALKANESULFONIC, CHLORO"/CN)

L9 10 SEA FILE=REGISTRY ABB=ON PLU=ON ("P-TOLUENESULFONIC ACID"/CN OR "P-TOLUENESULFONIC ACID ((4R)-2,2-DIMETHYL-1,3-DIOXOLAN-4-YLMETHYL ESTER"/CN OR "P-TOLUENESULFONIC ACID ((4S)-2,2-DIMETHYL-1,3-DIOXOLAN-4-YLMETHYL ESTER"/CN OR "P-TOLUENESULFONIC ACID (1-BENZYL-4-CYANO-4-PIPERIDYL)METHYL ESTER"/CN OR "P-TOLUENESULFONIC ACID (S)-2-METHYLBUTYL ESTER"/CN OR "P-TOLUENESULFONIC ACID B-ETHOXYETHYL ESTER"/CN OR "P-TOLUENESULFONIC ACID B-METHOXYETHYL ESTER"/CN OR "P-TOLUENESULFONIC ACID 1,2-DIAMINOETHANE SALT (2:1)"/CN OR "P-TOLUENESULFONIC ACID 1,6-DIAMINOHEXANE SALT (2:1)"/CN OR "P-TOLUENESULFONIC ACID 1-METHYLHEPTYL ESTER"/CN)

L11 STR



NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE

L12 SCR 2043
L14 9528 SEA FILE=REGISTRY SSS FUL L11 AND L12
L15 44277 SEA FILE=CAPLUS ABB=ON PLU=ON L1 OR L6 OR L14
L16 1 SEA FILE=REGISTRY ABB=ON PLU=ON "POTASSIUM HYDROXIDE"/CN
L17 1 SEA FILE=REGISTRY ABB=ON PLU=ON "SODIUM HYDROXIDE"/CN
L18 2 SEA FILE=REGISTRY ABB=ON PLU=ON TMAH/CN
L19 94179 SEA FILE=CAPLUS ABB=ON PLU=ON L16 OR L17 OR L18
L20 366 SEA FILE=CAPLUS ABB=ON PLU=ON L15 AND L19
L21 12 SEA FILE=CAPLUS ABB=ON PLU=ON L20 AND (PHOTORESIST OR RESIST)
L22 0 SEA FILE=CAPLUS ABB=ON PLU=ON L20 AND OVERCOAT? (5A) COMPOSITION?
N?
L23 22 SEA FILE=CAPLUS ABB=ON PLU=ON L20 AND COAT? (5A) COMPOSITION?
L24 33 SEA FILE=CAPLUS ABB=ON PLU=ON (L21 OR L22 OR L23)
L25 10417 SEA FILE=CAPLUS ABB=ON PLU=ON L8 OR L9
L27 84 SEA FILE=CAPLUS ABB=ON PLU=ON L15 AND L25

L28 6 SEA FILE=CAPLUS ABB=ON PLU=ON L27 AND (L19 OR (POTASSIUM OR SODIUM) (5A) HYDROXIDE)
L29 5 SEA FILE=CAPLUS ABB=ON PLU=ON L27 AND (POTASSIUM OR SODIUM) (5A) HYDROXIDE
L30 6 SEA FILE=CAPLUS ABB=ON PLU=ON L28 OR L29
L31 3 SEA FILE=CAPLUS ABB=ON PLU=ON L30 AND (COAT? OR ?RESIST)
L32 35 SEA FILE=CAPLUS ABB=ON PLU=ON L24 OR L31

=> d ti 1-35

L32 ANSWER 1 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Protective seed-coating composition

L32 ANSWER 2 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Nucleic-acid ink compositions for arraying onto a solid support

L32 ANSWER 3 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Coating compositions for formation of thin porous silica films with low refractive index

L32 ANSWER 4 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Pesticidal compositions for coating plant propagation material containing anthranilamides

L32 ANSWER 5 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Synthesis of new polymers for photoresist and lithographic printing applications

L32 ANSWER 6 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI 'Method for forming fine resist patterns with excellent dimensional uniformity

L32 ANSWER 7 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Absorption agents for hygienic materials with a high swelling capacity reduced tendency to cake

L32 ANSWER 8 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Multi-layer reaction mixtures and apparatuses for delivering a volatile component via a controlled exothermic reaction

L32 ANSWER 9 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Acrylic enteric coating compositions

L32 ANSWER 10 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Composition and process for coating tin oxide-based transparent conductive film

L32 ANSWER 11 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Composition for antireflection coating on photoresist film

- L32 ANSWER 12 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects
- L32 ANSWER 13 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Photoresist pattern formation, semiconductor device, and its manufacture by using the method
- L32 ANSWER 14 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Stabilized compositions containing benzimidazole compounds or their alkali metal salts and their enteric coated preparations
- L32 ANSWER 15 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Coating agents for oral formulations containing HMG-CoA reductase inhibitors
- L32 ANSWER 16 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Cyclized copolymer of methacrylic anhydride and an application to photoresist with photoacid generator
- L32 ANSWER 17 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Semiconductor device having fine patterns and its fabrication
- L32 ANSWER 18 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Metal thin-film pattern formation by electroless plating of photoresist
- L32 ANSWER 19 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Composition for the detection of electrophilic gases and methods of use thereof
- L32 ANSWER 20 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Enteric film coating compositions for coating pharmaceutical tablets
- L32 ANSWER 21 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Coating compositions for water-based ink-printable transparent sheets
- L32 ANSWER 22 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Resist pattern formation with pretreatment with aqueous solution
- L32 ANSWER 23 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Synthesis of new metal-free diazonium salts and their applications to microlithography
- L32 ANSWER 24 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI A body-fluid assay stick with an ink composition
- L32 ANSWER 25 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI A body fluid assay stick for glucose detection and protein detection

and/or pH determination, and a method for manufacturing the stick

L32 ANSWER 26 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI A pH determination ink composition containing a quaternary ammonium or amine salt and basic substance and a test stick for pH determination

L32 ANSWER 27 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Drain cleaner

L32 ANSWER 28 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Developers for positive-working photoresists

L32 ANSWER 29 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Ink-jet recording system

L32 ANSWER 30 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Processing photosensitive silver halide color photographic material

L32 ANSWER 31 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Image formation material and correction method

L32 ANSWER 32 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI High contrast photoresist developer

L32 ANSWER 33 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Colored pH-sensitive films and their uses

L32 ANSWER 34 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Preventing deposition in polymerization and polymerization reaction apparatus

L32 ANSWER 35 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
TI Visual recording

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L32 ANSWER 1 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2004:331752 CAPLUS
DOCUMENT NUMBER: 140:334101
TITLE: Protective seed-coating composition
INVENTOR(S): Lynch, John F.
PATENT ASSIGNEE(S): Mex.
SOURCE: U.S. Pat. Appl. Publ., 12 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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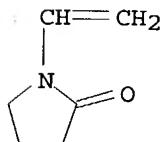
US 2004077498 A1 20040422 US 2003-610728 20030701
PRIORITY APPLN. INFO.: US 2002-393153P P 20020701
AB The seed coating composition has a first protective polymer film coating, which is nonphytotoxic, maintains oxygen exchange properties, and is hygroscopic. The composition also has a secondary growth-stimulating coating.
IT 1310-58-3, Potassium Hydroxide, biological studies
9003-39-8, Polyvinylpyrrolidone
RL: AGR (Agricultural use); BIOL (Biological study); USES (Uses)
(protective seed-coating composition containing)
RN 1310-58-3 CAPLUS
CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K- OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM A01N025-26
NCL 504100000
CC 5-3 (Agrochemical Bioregulators)
ST protective seed coating compn polymer fertilizer
phytohormone
IT Polyoxyalkylenes, uses
RL: MOA (Modifier or additive use); USES (Uses)
(plasticizer; protective seed-coating composition
containing)
IT Seed
(protective seed-coating composition)
IT Auxins
Cytokinins
Fertilizers
Hormones, plant
RL: AGR (Agricultural use); BIOL (Biological study); USES (Uses)
(protective seed-coating composition containing)
IT Lecithins
RL: MOA (Modifier or additive use); USES (Uses)

(surfactant; protective seed-coating composition containing)
IT 9002-89-5, Polyvinyl alcohol 9003-20-7, Polyvinyl acetate 9004-64-2,
Hydroxypropylcellulose 9004-67-5, Methylcellulose 9032-42-2,
Hydroxyethylmethylcellulose 25086-89-9 37353-59-6,
Hydroxymethylcellulose
RL: MOA (Modifier or additive use); USES (Uses)
(binder; protective seed-coating composition containing)
IT 56-81-5, Glycerin., uses 57-55-6, Propylene Glycol, uses 77-89-4,
Acetyltriethyl citrate 77-90-7, Acetyltributyl citrate 77-93-0,
Triethyl citrate 102-76-1, Glyceryl triacetate 109-43-3,
Dibutylsebacate 25322-68-3, Polyethylene glycol
RL: MOA (Modifier or additive use); USES (Uses)
(plasticizer; protective seed-coating composition
containing)
IT 57-13-6, Urea, biological studies 65-85-0, Benzoic acid, biological
studies 69-72-7, Salicylic acid., biological studies 77-06-5,
Gibberellic acid 574-85-6, Fluorazol 759-94-4 1071-83-6, Glyphosate
1310-58-3, Potassium Hydroxide, biological studies 1918-00-9,
Dicamba 4401-74-5, Urea phosphate 6484-52-2, Ammonium nitrate,
biological studies 7439-89-6, Iron, biological studies 7439-96-5,
Manganese, biological studies 7440-50-8, Copper, biological studies
7440-66-6, Zinc, biological studies 7440-70-2, Calcium, biological
studies 7447-40-7, Potassium chloride, biological studies 7487-88-9,
Magnesium sulfate, biological studies 7631-95-0, Sodium molybdate
7757-79-1, Potassium nitrate, biological studies 7778-80-5, ,Potassium
sulfate, biological studies 7783-20-2, Ammonium sulfate, biological
studies 9003-39-8, Polyvinylpyrrolidone 9004-38-0, Cellulose
acetate phthalate 9004-65-3, Hydroxypropylmethylcellulose 9011-16-9
9032-50-2, Methylcellulose phthalate 10124-31-9, Ammonium phosphate
10124-37-5, Calcium nitrate 10377-60-3, Magnesium nitrate 12027-67-7,
Ammonium Molybdate 13840-56-7, Sodium borate 15972-60-8, Alachlor
16068-46-5, Potassium phosphate 19045-66-0D, Thiocarbamic acid, salts
and esters 34256-82-1, Acetochlor. 37324-30-4, Hydroxypropylcellulose
phthalate 37764-25-3, N,N-Diallyl dichloroacetamide 51218-45-2,
Metolachlor 53237-50-6 74782-23-3, Oxabetrinil 78370-21-5,
Cyometrinil 98723-86-5, Hydroxymethyl cellulose phthalate 157480-63-2,
Hydroxyethyl methyl cellulose phthalate 681029-93-6, Carboxymethyl
cellulose phthalate
RL: AGR (Agricultural use); BIOL (Biological study); USES (Uses)
(protective seed-coating composition containing)
IT 151-21-3, Sodium lauryl sulfate, uses 9005-65-6, Polysorbate 80
9005-67-8, Polysorbate 60 106392-12-5
RL: MOA (Modifier or additive use); USES (Uses)
(surfactant; protective seed-coating composition containing)

L32 ANSWER 2 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2004:220075 CAPLUS
DOCUMENT NUMBER: 140:248187
TITLE: Nucleic-acid ink compositions for arraying onto a
solid support
INVENTOR(S): Pal, Santona
PATENT ASSIGNEE(S): USA

SOURCE: U.S. Pat. Appl. Publ., 17 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2004054160	A1	20040318	US 2002-244898	20020916
WO 2004024958	A1	20040325	WO 2003-US29086	20030916

W: JP
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, SE, SI, SK, TR

PRIORITY APPLN. INFO.: US 2002-244898 A 20020916
AB A medium or ink solution containing nucleic acid is provided for depositing onto

a solid support in the manufacture of biol. arrays. The medium has a composition

that comprises: about 30% to about 80% by volume of an organic solution comprising

dimethylsulfoxide (DMSO), ethylene glycol (EG), formamide, or a combination thereof; a buffer with a pH value of about 3.5-9.5; water; and nucleic acid, wherein the nucleic acid denatures to provide for more favorable hybridization. The buffer can be made from a solution that may contain acetate, citrate, citrate-phosphate, maleate, or succinate. The medium permits long-term storage of nucleic acids in solution without excessive degradation, which is a phenomenon associated with many conventional ink solns.

IT 1310-73-2, Sodium hydroxide, uses 38000-06-5, Polylysine
RL: NUU (Other use, unclassified); USES (Uses)

(nucleic-acid ink compns. for arraying onto a solid support)

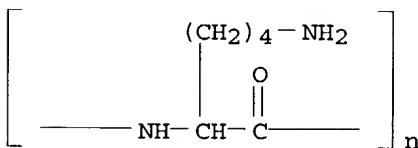
RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

RN 38000-06-5 CAPLUS

CN Poly[imino[(1S)-1-(4-aminobutyl)-2-oxo-1,2-ethanediyl]] (9CI) (CA INDEX NAME)



IC ICM C12Q001-68

ICS C07H021-04
NCL 536024300; 435006000
CC 3-1 (Biochemical Genetics)
ST nucleic acid ink compn arraying solid support
IT Surface
 (Aminated; nucleic-acid ink compns. for arraying onto a solid support)
IT Molecules
 (Multivalent; nucleic-acid ink compns. for arraying onto a solid support)
IT Polymers, uses
 RL: NUU (Other use, unclassified); USES (Uses)
 (Neutral; nucleic-acid ink compns. for arraying onto a solid support)
IT Solutions
 (Organic; nucleic-acid ink compns. for arraying onto a solid support)
IT Surface
 (Planar; nucleic-acid ink compns. for arraying onto a solid support)
IT Functional groups
 (anhydride group; nucleic-acid ink compns. for arraying onto a solid support)
IT DNA
 RL: ARG (Analytical reagent use); DEV (Device component use); PEP
 (Physical, engineering or chemical process); PYP (Physical process); ANST
 (Analytical study); PROC (Process); USES (Uses)
 (double-stranded; nucleic-acid ink compns. for arraying onto a solid support)
IT Adhesion, physical
Aggregation
Buffers
Cations
 Coating materials
Composition
Concentration (condition)
DNA microarray technology
Decomposition
Denaturation
Glass substrates
Inks
Membranes, nonbiological
Microarray technology
Nucleic acid hybridization
Precipitation (chemical)
Preservation
Printing (impact)
Solids
Solutions
Storage
Surface
Suspensions
Viscosity
Volume
Wettability
pH

(nucleic-acid ink compns. for arraying onto a solid support)
IT Nucleic acids
Oligonucleotides
RNA
RL: ARG (Analytical reagent use); DEV (Device component use); PEP (Physical, engineering or chemical process); PYP (Physical process); ANST (Analytical study); PROC (Process); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT Glass, uses
RL: DEV (Device component use); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT Histones
RL: NUU (Other use, unclassified); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT Inorganic compounds
RL: NUU (Other use, unclassified); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT Organic compounds, uses
RL: NUU (Other use, unclassified); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT Denaturation
(thermal; nucleic-acid ink compns. for arraying onto a solid support)
IT 6382-82-7, γ -Aminopropylsilane 9011-13-6, Styrene-maleic anhydride copolymer 13598-78-2D, Aminosilane, alkyl derivs.
RL: DEV (Device component use); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)
IT 60-00-4, EDTA, uses 64-19-7, Acetic acid, uses 67-68-5, DMSO, uses 71-44-3, Spermine 75-12-7, Formamide, uses 77-92-9, Citric acid, uses 107-21-1, Ethylene glycol, uses 110-15-6, Succinic acid, uses 110-16-7, 2-Butenedioic acid (2Z)-, uses 124-20-9, Spermidine 127-09-3, Sodiumacetate 994-36-5, Sodium citrate 1310-73-2, Sodium hydroxide, uses 7632-05-5, Sodiumphosphate 7732-18-5, Water, uses 14265-44-2, Phosphate, uses 14695-95-5 25104-18-1, Polylysine 38000-06-5, Polylysine
RL: NUU (Other use, unclassified); USES (Uses)
(nucleic-acid ink compns. for arraying onto a solid support)

L32 ANSWER 3 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:491332 CAPLUS
DOCUMENT NUMBER: 139:54384
TITLE: Coating compositions for formation
of thin porous silica films with low refractive index
INVENTOR(S): Sasaki, Yoro; Hanahata, Hiroyuki; Ioka, Takaaki
PATENT ASSIGNEE(S): Asahi Kasei Kabushiki Kaisha, Japan
SOURCE: PCT Int. Appl., 94 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2003052003 A1 20030626 WO 2002-JP13081 20021213
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH,
PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ,
UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD,
RU, TJ, TM
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, BG,
CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
PT, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML,
MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.: JP 2001-381084 A 20011214
JP 2002-45098 A 20020221

AB Title compns. comprise (a) fluidable SiO₂ precursors prepared by hydrolytic polycondensation of R₁aSi(OR₂)_{4-a} [R₁ = H, C₁-10 alkyl, C₆-10 aryl, vinyl, vinyl group-containing C₃-10 organic group, (meth)acryloyl-containing C₄-10 organic

group, epoxy group-containing C₃-10 organic group; R₂ = C₁-6 alkyl; n = 0-2] and/or (R₃O)₃SiR_{4-m}Si(OR₃)₃ (R₃ = C₁-6 alkyl; R₄ = C₁-6 alkylene, C₆-10 arylene; m = 0-1) in the presence of acid catalysts, (b) OH-containing or N-containing basic compds. forming 0.1 N aqueous solns. with a pH of ≥ 11 and 100° vapor pressure of ≤ 1.3 kPa at an amount of 0.0015-0.5 mol (based on the OH group or N atom) per 1-mol Si atom, and (c) the fluidable SiO₂ precursor-compatible organic compds. with a b.p. of ≥ 100°. A composition containing 80:20 MeSi(OEt)₃-Si(OEt)₄ copolymer (prepared in presence of H₃PO₄), polyoxyethylene di-Me ether, NaOH at 0.10 mol/Si, and H₂O/propylene glycol mono-Me ether solvent blend was spin coated on a Si wafer, cured at 100° for 1 min, soaked in 1:1 H₂O/EtOH blend, and dried at 100° for 1 min to form porous thin film showing reflective index 0.1%, transparency 99.0%, refractive index 1.210 at 1.95 eV, and pencil hardness HB.

IT 1310-73-2, Sodium hydroxide, uses

RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(alkoxysilane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

IT 9003-39-8, Poly(vinyl pyrrolidone)

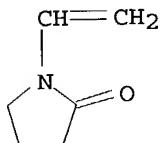
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(high b.p., polysiloxane-compatible; alkoxysilane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM C09D005-00
ICS C09D007-12; C09D183-02; C09D183-04; C09D183-14
CC 42-13 (Coatings, Inks, and Related Products)
Section cross-reference(s): 73, 74
ST alkoxy silane condensate basic compd coating formation thin silica film;
high boiling point compd polysiloxane formation porous silica film; low
refractive index porous thin silica film formation coating
IT Antireflective films
(alkoxysilane condensate-, basic compound- and high b.p. compound-containing
coatings for formation of thin porous SiO₂ film with low refractive
index)
IT Polysiloxanes, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM
(Technical or engineered material use); PREP (Preparation); USES (Uses)
(alkoxysilane condensate-, basic compound- and high b.p. compound-containing
coatings for formation of thin porous SiO₂ film with low refractive
index)
IT Amines, uses
Hydroxides (inorganic)
RL: PRP (Properties); TEM (Technical or engineered material use); USES
(Uses)
(alkoxysilane condensate-, basic compound- and high b.p. compound-containing
coatings for formation of thin porous SiO₂ film with low refractive
index)
IT Quaternary ammonium compounds, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(alkoxysilane condensate-, basic compound- and high b.p. compound-containing
coatings for formation of thin porous SiO₂ film with low refractive
index)
IT Polyoxyalkylenes, uses
RL: PRP (Properties); TEM (Technical or engineered material use); USES
(Uses)
(alkyl group-terminated, high b.p., polysiloxane-compatible;
alkoxysilane condensate-, basic compound- and high b.p. compound-containing
coatings for formation of thin porous SiO₂ film with low refractive
index).

- IT Transparent materials
 - (coatings; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT Carbohydrates, uses
 - Esters, uses
 - Polyamides, uses
 - Polycarbonates, uses
 - Polyesters, uses
 - RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 - (high b.p., polysiloxane-compatible; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT Cation exchangers
 - (hydrolytic polycondensation catalyst; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT Acids, uses
 - RL: CAT (Catalyst use); USES (Uses)
 - (hydrolytic polycondensation catalyst; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT Alcohols, uses
 - RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 - (polyhydric, high b.p., polysiloxane-compatible; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT Coating materials
 - (transparent; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT 88029-70-3P, Methyltriethoxysilane-tetraethoxysilane copolymer 512195-55-0P
 - RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 - (alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT 112-24-3, Triethylenetetramine 112-57-2, Tetraethylenepentamine 1310-73-2, Sodium hydroxide, uses 4499-86-9, Tetrapropylammonium hydroxide 9002-98-6 26913-06-4, Poly[imino(1,2-ethanediyl)]
 - RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 - (alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for formation of thin porous SiO₂ film with low refractive index)
- IT 64-17-5, Ethanol, uses 67-64-1, Acetone, uses
 - RL: NUU (Other use, unclassified); USES (Uses)
 - (aqueous blends, for extraction of high b.p. organic compds.; alkoxy silane condensate-, basic compound- and high b.p. compound-containing coatings for

formation of thin porous SiO₂ film with low refractive index)

IT 102-76-1, Glycerol triacetate 110-71-4, 1,2-Dimethoxyethane 9002-89-5,
Poly(vinyl alcohol) 9003-01-4, Polyacrylic acid 9003-05-8,
Polyacrylamide 9003-09-2, Methyl vinyl ether homopolymer
9003-39-8, Poly(vinyl pyrrolidone) 9004-34-6, Cellulose, uses
24991-55-7, Polyethylene glycol dimethyl ether 99788-44-0, Sucrose
triacetate
RL: PRP (Properties); TEM (Technical or engineered material use); USES
(Uses)
(high b.p., polysiloxane-compatible; alkoxy silane condensate-, basic
compound- and high b.p. compound-containing coatings for formation of thin
porous SiO₂ film with low refractive index)

IT 7664-38-2, Phosphoric acid, uses 135153-08-1, Diaion RCP 160H
RL: CAT (Catalyst use); USES (Uses)
(hydrolytic polycondensation catalyst; alkoxy silane condensate-, basic
compound- and high b.p. compound-containing coatings for formation of thin
porous SiO₂ film with low refractive index)

IT 7631-86-9P, Silica, uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or
engineered material use); PREP (Preparation); USES (Uses)
(porous thin films; alkoxy silane condensate-, basic compound- and high
b.p. compound-containing coatings for formation of thin porous SiO₂ film
with
low refractive index)

REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 4 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:242097 CAPLUS
DOCUMENT NUMBER: 138:267201
TITLE: Pesticidal compositions for coating
INVENTOR(S): plant propagation material containing anthranilamides
Berger, Richard Alan; Flexner, John Lindsey
PATENT ASSIGNEE(S): E. I. Du Pont de Nemours & Co., USA
SOURCE: PCT Int. Appl., 147 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2003024222	A1	20030327	WO 2002-US30302	20020910
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
RW:	GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, BG,			

CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
PT, SE, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR,
NE, SN, TD, TG

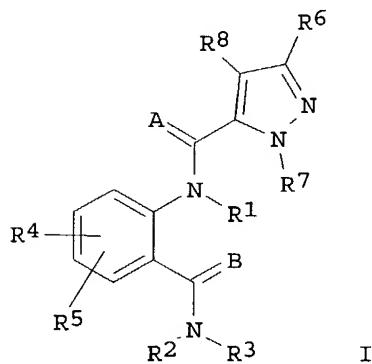
EP 1427285 A1 20040616 EP 2002-775972 20020910

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK

PRIORITY APPLN. INFO.: US 2001-323941P P 20010921
WO 2002-US30302 W 20020910

OTHER SOURCE(S): MARPAT 138:267201

GI



AB An invertebrate pest control composition for coating a propagule comprises (1) a biol. effective amount of an anthranilamide compds. I (Markush included), an N-oxide thereof or an agriculturally suitable salt thereof, and (2) a film former or adhesive agent. Arthropodicidal composition containing anthranilamide compds. I may further comprise addnl. biol. active compds. selected from arthropodicides of the group consisting of pyrethroids, carbamates, neonicotinoids, neuronal sodium channel blockers, insecticidal macrocyclic lactones, γ -aminobutyric acid (GABA) antagonists, insecticidal ureas, and juvenile hormone mimics, and fungicides. The propagule is a seed of cotton, maize, soybean, rice, etc., or a rhizome, tuber, bulb or corm, or viable division thereof, of potato, sweet potato, garden onion, tulip, daffodil, crocus hyacinth, etc., or is a stem or leaf cutting.

IT 9003-39-8, Polyvinylpyrrolidone

RL: AGR (Agricultural use); TEM (Technical or engineered material use);

BIOL (Biological study); USES (Uses)

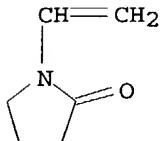
(in pesticidal compns. for plant propagation material containing anthranilamides)

RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IT 1310-58-3, Potassium hydroxide, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of anthranilamide compds. as pesticides for plant propagation material)
RN 1310-58-3 CAPLUS
CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K—OH

IC ICM A01N043-56
CC 5-4 (Agrochemical Bioregulators)
Section cross-reference(s): 28
ST arthropodicide insecticide anthranilamide prepn propagule seed
IT Insecticides
(carbamate; in pesticidal compns. for plant propagation material containing anthranilamides)
IT Leaf
(cutting; pesticidal compns. containing anthranilamides for treatment of)
IT Eubacteria
Fungi
Virus
(entomopathogenic; in pesticidal compns. for plant propagation material containing anthranilamides)
IT Adhesives
Bacillus thuringiensis aizawai
Bacillus thuringiensis kurstaki
Baculoviridae
Coating materials
Fungicides
GABA antagonists
Gums and Mucilages
Latex
(in pesticidal compns. for plant propagation material containing anthranilamides)
IT Macrolides
RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)

- IT Acrylic polymers, biological studies
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Fats and Glyceridic oils, biological studies
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Gelatins, biological studies
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Oils
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Polyoxyalkylenes, biological studies
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Polysaccharides, biological studies
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Proteins
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Shellac
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Waxes
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Zeins
RL: AGR (Agricultural use); TEM (Technical or engineered material use); BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing anthranilamides)
- IT Juvenile hormones
RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL

(Biological study); USES (Uses)
(mimics; in pesticidal compns. for plant propagation material containing anthranilamides)

IT Melon (plant)
(musk-; pesticidal compns. containing anthranilamides for plant propagation material of)

IT Insecticides
(neonicotinoid; in pesticidal compns. for plant propagation material containing anthranilamides)

IT Onion (*Allium cepa*)
(ornamental; pesticidal compns. containing anthranilamides for plant propagation material of)

IT Anemone
Armeria
Avena sativa
Begonia tuberhybrida
Beta vulgaris
Brassica juncea
Brassica nigra
Brassica oleracea capitata
Calla
Capsicum
Chionodoxa
Chrysanthemum
Coleus
Cosmos (plant)
Crocus (plant)
Cucumis sativus
Cyclamen
Dahlia (plant)
Daucus carota
Durum wheat
Freesia
Geranium (horticultural common name)
Gerbera
Gladiolus
Gloxinia (genus)
Gossypium hirsutum
Gypsophila elegans
Hordeum vulgare
Hyacinth (plant)
Impatiens
Iris (plant)
Lactuca sativa
Liatris spicata
Lilium
Linum usitatissimum
Lisianthus
Lycopersicon esculentum
Marigold
Medicago sativa
Muscari racemosum

Narcissus
Nicotiana tabacum
Onion (Allium cepa)
Oryza sativa
Oxalis corniculata
Peanut (Arachis hypogaea)
Petunia
Phaseolus lunatus
Phaseolus vulgaris
Pisum sativum
Puschkinia libanotica
Rapeseed
Scabiosa atropurpurea
Secale cereale
Snapdragon (Antirrhinum)
Solanum melongena
Solanum tuberosum
Sorghum
Soybean (Glycine max)
Squash (Cucurbita)
Squill (plant)
Sunflower
Sweet potato
Tulip
Turnip
Vicia faba
Viola wittrockiana
Watermelon (Citrullus lanatus)
Yam (Dioscorea)
Yarrow (Achillea)
Zea mays
Zinnia
Zizania
 (pesticidal compns. containing anthranilamides for plant propagation material of)
IT Bulb (plant)
 Seed
 Stem
 Tuber (plant organ)
 (pesticidal compns. containing anthranilamides for treatment of)
IT Pyrethrins
 RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL (Biological study); USES (Uses)
 (pyrethroids; in pesticidal compns. for plant propagation material containing anthranilamides)
IT Stem
 (rhizome; pesticidal compns. containing anthranilamides for treatment of)
IT Ion channel blockers
 (sodium; in pesticidal compns. for plant propagation material containing anthranilamides)
IT Toxins
 RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL

(Biological study); USES (Uses)					
(δ-endotoxins; in pesticidal compns. for plant propagation material containing anthranilamides)					
IT	362637-52-3	362637-54-5	362637-55-6	362637-56-7	362637-57-8
	362637-58-9	362637-59-0	362637-60-3	362637-61-4	362637-62-5
	362637-63-6	362637-64-7	362637-65-8	362637-66-9	362637-67-0
	362637-68-1	362637-69-2	362637-71-6	362637-72-7	362637-73-8
	362637-74-9	362637-75-0	362637-76-1	362637-77-2	362637-78-3
	362637-79-4	362637-80-7	362637-81-8	362637-82-9	362637-83-0
	362637-84-1	362637-85-2	362637-86-3	362637-87-4	362637-88-5
	362637-89-6	362637-90-9	362637-91-0	362637-92-1	362637-93-2
	362637-94-3	362637-95-4	362637-96-5	362637-97-6	362637-98-7
	362638-06-0	362638-07-1	362638-08-2	362638-09-3	362638-10-6
	362638-11-7	362638-12-8	362638-13-9	362638-14-0	362638-15-1
	362638-16-2	362638-17-3	362638-18-4	362638-19-5	362638-20-8
	362638-21-9	362638-22-0	362638-23-1	362638-24-2	362638-25-3
	362638-26-4	362638-27-5	362638-28-6	362638-29-7	362638-31-1
	362638-32-2	362638-33-3	362638-34-4	362638-35-5	362638-36-6
	362638-37-7	362638-38-8	362638-39-9	362638-40-2	362638-41-3
	362638-42-4	362638-43-5	362638-44-6	362638-45-7	362638-46-8
	362638-47-9	362638-48-0	362638-49-1	362638-50-4	362638-51-5
	362638-52-6	362638-53-7	362638-54-8	362638-55-9	362638-56-0
	362638-57-1	362638-58-2	362638-59-3	362638-60-6	362638-63-9
	362638-64-0	362638-65-1	362638-66-2	362638-67-3	362638-68-4
	362638-69-5	362638-70-8	362638-71-9	362638-72-0	362638-73-1
	362638-74-2	362638-75-3	362638-76-4	362638-77-5	362638-78-6
	362638-79-7	362638-80-0	362638-81-1	362638-82-2	362638-83-3
	362638-84-4	362638-85-5	362638-86-6	362638-87-7	362638-88-8
	362638-89-9	362638-90-2	362638-91-3	362638-92-4	362638-93-5
	362638-94-6	362638-95-7	362638-96-8	362638-97-9	362638-98-0
	362638-99-1	362639-00-7	362639-01-8	362639-02-9	362639-03-0
	362639-04-1	362639-05-2	362639-06-3	362639-07-4	362639-09-6
	362639-10-9	362639-11-0	362639-12-1	362639-13-2	362639-14-3
	362639-15-4	362639-16-5	362639-17-6	362639-18-7	362639-19-8
	362639-20-1	362639-21-2	362639-22-3	362639-23-4	362639-25-6
	362639-26-7	362639-27-8	362639-28-9	362639-29-0	362639-30-3
	362639-31-4	362639-32-5	362639-33-6	362639-34-7	362639-35-8
	362639-36-9	362639-37-0	362639-38-1	362639-40-5	362639-41-6
	362639-42-7	362639-43-8	362639-44-9	362639-45-0	362639-46-1
	362639-47-2	362639-48-3	362639-49-4	362639-50-7	362639-51-8
	362639-52-9	362639-53-0	362639-54-1	362639-55-2	362639-56-3
	362639-57-4	362639-58-5	362639-59-6	362639-60-9	362639-61-0
	362639-63-2	362639-64-3	362639-65-4	362639-66-5	362639-67-6
	362639-68-7	362639-69-8	362639-70-1	362639-71-2	362639-73-4
	362639-74-5	362639-75-6	362639-76-7	362639-77-8	362639-78-9
	362639-79-0	362639-80-3	362639-81-4	362639-82-5	362639-85-8
	362640-64-0	362640-65-1	500005-50-5	500005-52-7	500005-53-8
	500005-54-9	500005-55-0	500005-56-1	500005-57-2	500005-58-3
	500005-59-4	500005-64-1	500005-65-2	500005-69-6	500005-70-9
	500005-71-0	500005-72-1			

RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL

(Biological study) ; USES (Uses)

(anthranilamide compds. as pesticides for plant propagation material)

IT	500005-73-2	500005-74-3	500005-75-4	500005-76-5	500005-77-6
	500005-78-7	500005-79-8	500005-80-1	500005-81-2	500005-82-3
	500005-84-5	500005-85-6	500005-86-7	500005-87-8	500005-88-9
	500005-89-0	500005-90-3	500005-94-7	500005-95-8	500005-97-0
	500005-98-1	500005-99-2	500006-00-8	500006-01-9	500006-02-0
	500006-03-1	500006-04-2	500006-05-3	500006-06-4	500006-07-5
	500006-08-6	500006-09-7	500006-10-0	500006-11-1	500006-12-2
	500006-13-3	500006-14-4	500006-15-5	500006-16-6	500006-17-7
	500006-18-8	500006-19-9	500006-20-2	500006-21-3	500006-22-4
	500006-23-5	500006-24-6	500006-25-7	500006-26-8	500006-27-9
	500006-29-1	500006-30-4	500006-31-5	500006-32-6	500006-33-7
	500006-34-8	500006-35-9	500006-36-0	500006-37-1	500006-39-3
	500006-41-7	500006-43-9	500006-45-1	500006-47-3	500006-49-5
	500006-50-8	500006-51-9	500006-52-0	500006-53-1	500006-54-2
	500006-55-3	500006-56-4	500006-57-5	500006-58-6	500006-59-7
	500006-60-0	500006-61-1	500006-62-2	500006-63-3	500006-64-4
	500006-65-5	500006-66-6	500006-67-7	500006-68-8	500006-69-9
	500006-70-2	500006-71-3	500006-72-4	500006-73-5	500006-74-6
	500006-75-7	500006-76-8	500006-78-0	500006-79-1	500006-80-4
	500006-81-5	500006-82-6	500006-83-7	500006-84-8	500006-85-9
	500006-86-0	500006-87-1	500006-88-2	500006-89-3	500006-90-6
	500006-91-7	500006-92-8	500006-93-9	500006-94-0	500006-95-1
	500006-96-2	500006-97-3	500006-98-4	500006-99-5	500007-00-1
	500007-01-2	500007-02-3	500007-03-4	500007-04-5	500007-05-6
	500007-07-8	500007-08-9	500007-09-0	500007-10-3	500007-11-4
	500007-12-5	500007-13-6	500007-14-7	500007-15-8	500007-16-9
	500007-17-0	500007-20-5	500007-21-6	500007-23-8	500007-25-0
	500007-26-1	500007-27-2	500007-28-3	500007-29-4	500007-30-7
	500007-31-8	500007-32-9	500007-33-0	500007-34-1	500007-35-2
	500007-36-3	500007-37-4	500007-38-5	500007-39-6	500007-40-9
	500007-41-0	500007-42-1	500007-43-2	500007-44-3	500007-45-4
	500007-46-5	500007-47-6	500007-48-7	500007-49-8	500007-50-1
	500007-51-2	500007-53-4	500007-54-5	500007-55-6	500007-56-7
	500007-57-8	500007-58-9	500007-59-0	500007-60-3	500007-61-4
	500007-62-5	500007-63-6	500007-64-7	500007-65-8	500007-67-0
	500007-68-1	500007-69-2	500007-70-5	500007-71-6	500007-72-7
	500007-73-8	500007-74-9	500007-75-0	500007-76-1	500007-77-2
	500007-78-3	500007-80-7	500007-81-8	500007-82-9	500007-83-0
	500007-84-1	500007-85-2	500007-87-4	500007-88-5	500007-89-6
	500007-90-9	500007-91-0	500007-92-1	500007-93-2	500007-94-3
	500007-95-4	500007-96-5	500007-97-6	500008-02-6	500008-03-7
	500008-04-8	500008-05-9	500008-06-0	500008-07-1	500008-10-6
	500008-11-7	500008-12-8	500008-14-0	500008-18-4	500008-19-5
	500008-20-8	500008-21-9	500008-23-1	500008-25-3	500008-27-5
	500008-29-7	500008-30-0	500008-32-2	500008-34-4	500008-35-5
	500008-36-6	500008-37-7	500008-39-9	500008-41-3	500008-42-4
	500008-47-9	500008-49-1	500008-51-5	500008-53-7	500008-54-8
	500008-55-9	500008-56-0			

RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL (Biological study); USES (Uses)

(anthranilamide compds. as pesticides for plant propagation material)					
IT	500008-57-1	500008-58-2	500008-59-3	500008-64-0	500008-66-2
	500008-67-3	500008-68-4	500008-69-5	500008-70-8	500008-71-9
	500008-72-0	500008-73-1	500008-74-2	500008-75-3	500008-76-4
	500008-77-5	500008-79-7	500008-80-0	500008-81-1	500008-82-2
	500008-84-4	500008-85-5	500008-86-6	500008-87-7	500008-88-8
	500008-89-9	500008-90-2	500008-91-3	500008-92-4	500008-93-5
	500008-94-6	500008-95-7	500008-98-0	500008-99-1	500009-00-7
	500009-01-8	500009-03-0	500009-04-1	500009-05-2	500009-06-3
	500009-07-4	500009-08-5	500009-09-6	500009-10-9	500009-11-0
	500009-12-1	500009-14-3	500009-16-5	500009-18-7	500009-20-1
	500009-21-2	500009-23-4	500009-25-6	500009-26-7	500009-27-8
	500009-28-9	500009-29-0	500009-30-3	500009-31-4	500009-32-5
	500009-33-6	500009-34-7	500009-35-8	500009-36-9	500009-37-0
	500009-38-1	500009-39-2	500009-40-5	500009-41-6	500009-42-7
	500009-43-8	500009-44-9	500009-45-0	500009-46-1	500009-47-2
	500009-49-4	500009-50-7	500009-51-8	500009-52-9	500009-53-0
	500009-54-1	500009-55-2	500009-56-3	500009-57-4	500009-58-5
	500009-59-6	500009-60-9	500009-61-0	500009-62-1	500009-65-4
	500009-66-5	500009-67-6	500009-68-7	500009-69-8	500009-77-8
	500009-78-9	500009-79-0	500009-82-5	500009-83-6	500009-84-7
	500009-86-9	500009-87-0	500009-88-1	500009-89-2	500009-90-5
	500009-91-6	500009-92-7	500009-93-8	500009-94-9	500009-95-0
	500009-96-1	500009-97-2	500009-98-3	500009-99-4	500010-00-4
	500010-01-5	500010-02-6	500010-03-7	500010-04-8	500010-05-9
	500010-06-0	500010-07-1	500010-08-2	500010-09-3	500010-11-7
	500010-12-8	500010-13-9	500010-14-0	500010-15-1	500010-16-2
	500010-17-3	500010-18-4	500010-19-5	500010-20-8	500010-21-9
	500010-22-0	500010-23-1	500010-25-3	500010-26-4	500010-27-5
	500010-28-6	500010-29-7	500010-30-0	500010-31-1	500010-32-2
	500010-33-3	500010-34-4	500010-35-5	500010-36-6	500010-37-7
	500010-38-8	500010-39-9	500010-40-2	500010-41-3	500010-42-4
	500010-43-5	500010-44-6	500010-45-7	500010-46-8	500010-47-9
	500010-48-0	500010-49-1	500010-50-4	500010-51-5	500010-52-6
	500010-53-7	500010-54-8	500010-55-9	500010-56-0	500010-57-1
	500010-58-2	500010-59-3	500010-60-6	500010-61-7	500010-62-8
	500010-63-9	500010-64-0	500010-65-1	500010-67-3	500010-68-4
	500010-69-5	500010-70-8	500010-71-9	500010-72-0	500010-73-1
	500010-74-2	500010-75-3	500010-76-4	500010-77-5	500010-79-7
	500010-80-0	500010-81-1	500010-82-2	500010-83-3	500010-84-4
	500010-85-5	500010-86-6	500010-87-7	500010-88-8	500010-89-9
	500010-90-2	500010-91-3	500010-92-4	500010-93-5	500010-94-6
	500010-95-7	500010-96-8	500010-97-9	500010-98-0	500010-99-1
	500011-00-7	500011-01-8	500011-02-9	500011-04-1	500011-05-2
	500011-06-3	500011-07-4	500011-08-5	500011-10-9	500011-11-0
	500011-12-1	500011-13-2	500011-14-3	500011-15-4	500011-16-5
	500011-17-6	500011-18-7	500011-19-8	500011-20-1	500011-21-2
	500011-22-3	500011-23-4	500011-24-5	500011-25-6	500011-26-7
	500011-27-8	500011-28-9			

RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL (Biological study); USES (Uses)

(anthranilamide compds. as pesticides for plant propagation material)

IT 500011-29-0 500011-31-4 500011-37-0 500011-38-1 500011-39-2
 500011-40-5 500011-41-6 500011-42-7 500011-43-8 500011-44-9
 500011-45-0 500011-46-1 500011-47-2 500011-48-3 500011-49-4
 500011-50-7 500011-51-8 500011-52-9 500011-53-0 500011-54-1
 500011-55-2 500011-56-3 500011-57-4 500011-58-5 500011-59-6
 500011-60-9 500011-61-0 500011-62-1 500011-63-2 500011-64-3
 500011-80-3 503163-52-8 503163-54-0 503163-56-2 503163-66-4
 RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL (Biological study); USES (Uses)
 (anthranilamide compds. as pesticides for plant propagation material)

IT 362639-39-2 362639-72-3 500005-60-7 500005-61-8 500005-62-9
 500005-63-0 500005-66-3 500005-67-4 500005-68-5 500005-83-4
 500005-91-4 500005-92-5 500005-93-6 500005-96-9 500006-28-0
 500007-18-1 500007-19-2 500007-22-7 500007-98-7 500007-99-8
 500008-13-9 500009-19-8 500009-22-3 500009-24-5 500009-70-1
 500009-71-2 500009-72-3 500009-73-4 500009-74-5 500009-75-6
 500009-76-7 500009-85-8 500010-66-2 500011-03-0 500011-09-6
 500011-30-3 500011-32-5 500011-33-6 500011-35-8 500011-36-9
 500011-65-4 500011-66-5 500011-67-6 500011-68-7 500011-69-8
 500011-70-1 500011-71-2 500011-72-3 500011-73-4 500011-74-5
 500011-75-6 500011-76-7 500011-77-8 500011-78-9 500011-79-0
 503163-58-4 503163-61-9 503163-64-2
 RL: AGR (Agricultural use); BSU (Biological study, unclassified); PRP (Properties); BIOL (Biological study); USES (Uses)
 (anthranilamide compds. as pesticides for plant propagation material)

IT 52-68-6 56-38-2 57-13-6D, Urea, derivs. 60-51-5, Dimethoate
 72-43-5 76-87-9, Fentin hydroxide 83-79-4 86-50-0, Azinphos-methyl
 99-30-9, Dicloran 108-62-3 115-29-7 115-32-2 116-06-3 121-75-5
 133-06-2, Captan 133-07-3, Folpet 137-26-8, Thiram 148-79-8,
 Thiabendazole 298-00-0 298-02-2 333-41-5, Diazinon 510-15-6
 732-11-6 900-95-8, Fentin acetate 944-22-9 950-37-8 1332-40-7,
 Copper oxychloride 1563-66-2, Carbofuran 1897-45-6, Chlorothalonil
 2079-00-7, Blasticidin-S 2227-17-0 2310-17-0 2312-35-8 2425-06-1,
 Captafol 2439-01-2 2439-10-3, Dodine 2675-77-6, Chloroneb
 2921-88-2, Chlorpyrifos 5598-13-0, Chlorpyrifos-methyl 6585-53-1,
 Ferric methanearsonate 6923-22-4 6980-18-3, Kasugamycin 7440-50-8D,
 Copper, salts 7704-34-9, Sulfur, biological studies 8011-63-0,
 Bordeaux mixture 8018-01-7, Mancozeb 10265-92-6 10605-21-7,
 Carbendazim 11141-17-6, Azadirachtin 12427-38-2, Maneb 13071-79-9
 13121-70-5 13171-21-6 13356-08-6 16752-77-5 17109-49-8, Edifenphos
 17804-35-2, Benomyl 22224-92-6 22248-79-9 23103-98-2 23135-22-0
 23564-05-8, Thiophanate-methyl 24579-73-5, Propamocarb 25311-71-1
 26087-47-8, Iprobenfos 27605-76-1, Probenazole 30560-19-1, Acephate
 33089-61-1 35367-38-5, Diflubenzuron 35400-43-2 36734-19-7,
 Iprodione 39148-24-8, Fosetylaluminum 39515-41-8 40596-69-8
 41198-08-7 41814-78-2, Tricyclazole 43121-43-3, Triadimefon
 50471-44-8, Vinclozolin 50512-35-1, Isoprothiolane 50642-14-3,
 Validamycin 51630-58-1 52207-48-4 52315-07-8, Cypermethrin
 52645-53-1 52918-63-5, Deltamethrin 53112-28-0, Pyrimethanil
 55219-65-3, Triadimenol 55814-41-0, Mepronil 57369-32-1, Pyroquilon
 57646-30-7, Furalaxyl 57837-19-1, Metalaxyl 57966-95-7, Cymoxanil
 58842-20-9 59669-26-0 60168-88-9, Fenarimol 60207-90-1,

Propiconazole 62850-32-2 62865-36-5, Diclomezine 63837-33-2,
Diofenolan 64628-44-0 66063-05-6, Pencycuron 66215-27-8, Cyromazine
66230-04-4 66246-88-6, Penconazole 66332-96-5, Flutolanil 66841-25-6
67306-00-7, Fenpropidin 67564-91-4, Fenpropimorph 67747-09-5,
Prochloraz 68085-85-8, Cyhalothrin 68359-37-5, Cyfluthrin
69327-76-0, Buprofezin 70124-77-5 70630-17-0, Mefenoxam 71422-67-8,
Chlorfluazuron 71751-41-2, Abamectin 72490-01-8 73989-17-0,
Avermectin 74738-17-3, Fenpiclonil 76674-21-0, Flutriafol
77732-09-3, Oxadixyl 78587-05-0 79538-32-2 79622-59-6, Fluazinam
79983-71-4, Hexaconazole 80060-09-9, Diafenthiuron 82657-04-3,
Bifenthrin 83121-18-0 83657-18-5, Diniconazole-M 83657-24-3,
Diniconazole 84466-05-7, Amidoflumet 85509-19-9, Flusilazole
86479-06-3 88283-41-4, Pyrifenoxy 88671-89-0, Myclobutanil 91465-08-6
94361-06-5, Cyproconazole 95737-68-1 96489-71-3 101463-69-8
102851-06-9 103055-07-8 104030-54-8, Carpropamid 107534-96-3,
Tebuconazole 110488-70-5, Dimethomorph 111988-49-9 112226-61-6
112281-77-3, Tetraconazole 112410-23-8 114369-43-6, Fenbuconazole
116255-48-2, Bromuconazole 116714-46-6 118134-30-8, Spiroxamine
119168-77-3 119446-68-3, Difenoconazole 119791-41-2, Emamectin
120068-37-3 120928-09-8 121451-02-3 121552-61-2, Cyprodinil
122453-73-0, Chlorfenapyr 123312-89-0 123572-88-3, Furametpyr
124495-18-7, Quinoxifen 125116-23-6, Metconazole 125225-28-7,
Ipconazole 126448-41-7, Acibenzolar 130000-40-7, Thifluzamide
131341-86-1, Fludioxonil 131807-57-3, Famoxadone 131860-33-8,
Azoxystrobin 131983-72-7, Triticonazole 133408-50-1, Metominostrobin
133855-98-8, Epoxiconazole 134098-61-6 136426-54-5, Fluquinconazole
138261-41-3 139920-32-4, Dicloctemet 140923-17-7, SZX0722
141517-21-7, Trifloxystrobin 143390-89-0, Kresoxim-methyl 143807-66-3,
Chromafenozide 149877-41-8, Bifenazate 149961-52-4, Dimoxystrobin
153233-91-1 153719-23-4 154025-04-4, Flumetover 156052-68-5, RH 7281
158062-67-0 160430-64-8, Acetamiprid 161050-58-4 161326-34-7
168316-95-8, Spinosad 170015-32-4 173584-44-6 175013-18-0,
Pyraclostrobin 178928-70-6, Prothioconazole 179101-81-6 180409-60-3,
Cyflufenamid 181587-01-9 188425-85-6, Nicobifen 189278-12-4,
Proquinazid 210880-92-5, Clothianidin 211867-47-9, SYP-L190
220899-03-6, Metrafenone 223580-51-6, Tiadinil 248593-16-0,
Orysastrobin 283594-90-1 361377-29-9, Fluoxastrobin
RL: AGR (Agricultural use); BSU (Biological study, unclassified); BIOL
(Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing
anthranilamides)

IT 75-35-4D, Vinylidene chloride, polymers and copolymers 79-41-4D,
Methylacrylic acid, imide derivs. 79-41-4D, Acrylimide, polymers and
copolymers, imide derivs. 8062-15-5, Lignosulfonate 9000-01-5, Gum
arabic 9000-30-0, Guar gum 9000-36-6, Karaya gum 9000-65-1,
Tragacanth gum 9002-89-5 9002-89-5D, Polyvinyl alcohol, copolymers
9003-09-2, Polyvinyl methyl ether 9003-20-7D, Polyvinyl acetate,
derivs., copolymers 9003-39-8, Polyvinylpyrrolidone 9004-32-4,
Carboxymethylcellulose 9004-34-6D, Cellulose, derivs. 9004-53-9,
Dextrins 9004-57-3, Ethylcellulose 9004-64-2, Hydroxypropylcellulose
9004-67-5D, Methylcellulose, derivs. 9005-25-8D, Starch, derivs.
9005-32-7, Alginic acid 9010-98-4, Polychloroprene 9011-16-9

9012-76-4, Chitosan 9050-36-6, Malto-dextrin 25086-89-9 25322-68-3,
Polyethylene oxide 26022-14-0, Polyhydroxyethyl acrylate 30811-69-9,
Polyvinylacrylate 37353-59-6D, Hydroxymethylcellulose, derivs.
69670-80-0, Hydroxymethylpropylcellulose
RL: AGR (Agricultural use); TEM (Technical or engineered material use);
BIOL (Biological study); USES (Uses)
(in pesticidal compns. for plant propagation material containing
anthranilamides)

IT 362637-53-4P 362637-70-5P 362638-30-0P 362639-62-1P 438450-41-0P,
N-[4-Chloro-2-methyl-6-[(methylamino)carbonyl]phenyl]-1-(3-chloro-2-
pyridinyl)-3-(trifluoromethyl)-1H-pyrazole-5-carboxamide 500008-00-4P
500008-44-6P 500008-45-7P 500008-60-6P 500008-62-8P 500010-10-6P
RL: AGR (Agricultural use); BSU (Biological study, unclassified); SPN
(Synthetic preparation); BIOL (Biological study); PREP (Preparation); USES
(Uses)
(preparation of anthranilamide compds. as pesticides for plant propagation
material)

IT 129585-50-8P
RL: BYP (Byproduct); SPN (Synthetic preparation); PREP (Preparation)
(preparation of anthranilamide compds. as pesticides for plant propagation
material)

IT 74-89-5, Methylamine, reactions 75-03-6, Iodoethane 75-31-0,
Isopropylamine, reactions 76-05-1, Trifluoroacetic acid, reactions
79-37-8, Oxalyl chloride 98-59-9, p-Toluenesulfonyl chloride 100-63-0,
Phenylhydrazine 109-72-8, n-Butyllithium, reactions 112-02-7,
Cetyltrimethylammonium chloride 121-44-8, Triethylamine, reactions
124-63-0, Methanesulfonyl chloride 128-09-6, N-Chlorosuccinimide
367-57-7 421-50-1, 1,1,1-Trifluoroacetone 503-38-8, Trichloromethyl
chloroformate 541-41-3, Ethyl chloroformate 584-08-7, Potassium
carbonate 630-25-1, 1,2-Dibromotetrachloroethane 1310-58-3,
Potassium hydroxide, reactions 2402-77-9, 2,3-Dichloropyridine
4111-54-0, Lithium diisopropylamide 4389-45-1, 2-Amino-3-methylbenzoic
acid 4755-77-5, Ethyl chlorooxacetate 5437-38-7, 3-Methyl-2-
nitrobenzoic acid 6226-25-1, 2,2,2-Trifluoroethyl
trifluoromethanesulfonate 7087-68-5, N,N-Diisopropylethylamine
7664-93-9, Sulfuric acid, reactions 7789-69-7, Phosphorus pentabromide
10025-87-3, Phosphorus oxychloride 10035-10-6, Hydrogen bromide,
reactions 14521-80-3, 3-Bromopyrazole 20154-03-4, 3-
Trifluoromethylpyrazole 22206-57-1, Tetrabutylammonium fluoride hydrate
22841-92-5 65753-47-1, 2-Chloro-3-trifluoromethylpyridine 66176-17-8,
3-Methylisatoic anhydride 133228-21-4 458543-79-8 499790-43-1
500011-81-4 500011-88-1 500011-94-9
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of anthranilamide compds. as pesticides for plant propagation
material)

IT 14339-33-4P, 3-Chloropyrazole 20776-67-4P, 2-Amino-3-methyl-5-
chlorobenzoic acid 68289-10-1P, 2-Amino-3-methyl-N-(1-
methylethyl)benzamide 120374-68-7P 128694-66-6P 362640-53-7P,
3-Methyl-N-(1-methylethyl)-2-nitrobenzamide 362640-58-2P 362640-59-3P
362640-60-6P 362640-61-7P 362640-62-8P 438450-38-5P,
3-Chloro-2-[3-(trifluoromethyl)-1H-pyrazol-1-yl]pyridine 438450-39-6P
438450-40-9P, 6-Chloro-2-[1-(3-chloro-2-pyridinyl)-3-(trifluoromethyl)-1H-

pyrazol-5-yl]-8-methyl-4H-3,1-benzoxazin-4-one 458543-77-6P
458543-78-7P 499790-45-3P 499790-46-4P 500011-82-5P 500011-83-6P
500011-84-7P 500011-85-8P 500011-86-9P 500011-87-0P 500011-89-2P
500011-90-5P 500011-91-6P 500011-92-7P 500011-95-0P 500011-96-1P
500011-97-2P 500011-98-3P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(preparation of anthranilamide compds. as pesticides for plant propagation material)

REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 5 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2002:753405 CAPLUS

DOCUMENT NUMBER: 138:114951

TITLE: Synthesis of new polymers for photoresist and lithographic printing applications

AUTHOR(S): Davidson, K.; El-Attawy, S.; El-Gamal, M.; Khattab, M. A.; El-Demerdach, A. M.

CORPORATE SOURCE: The Polymer Centre, Lancaster University, Lancaster, LA1 4YA, UK

SOURCE: High Performance Polymers (2002), 14(1), 3-15
CODEN: HPPOEX; ISSN: 0954-0083

PUBLISHER: Sage Publications

DOCUMENT TYPE: Journal

LANGUAGE: English

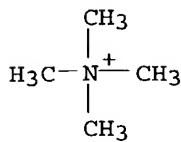
AB Lithog. resist materials based on copolymers and/or terpolymers have been synthesized. These materials are comprised of one component to induce water solubility, such as N-vinylpyrrolidinone (NVP) or N,N-di-methylacrylamide (DMAC); and another material to give the photoactive response, in this case allyl glycidyl ether (AGE) or glycidyl methacrylate (GMA). Copolymers and terpolymers of various compns. have been prepared by free radical copolymer. Cationically initiated photocrosslinking was induced using mixed arylsulfonium hexafluoroantimonate (MAS+-SbF6-) as a photoacid generating (PAG) species.

IT 75-59-2, Tetramethylammonium hydroxide

RL: NUU (Other use, unclassified); USES (Uses)
(developer; lithog. characterization of allyl glycidyl ether copolymers with water soluble monomers for photoresist applications)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



IT 282088-61-3P, Allyl glycidyl ether-N,N-dimethylacrylamide copolymer 488099-29-2P, Allyl glycidyl ether-N,N-dimethylacrylamide-glycidyl methacrylate copolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (preparation and characterization of allyl glycidyl ether copolymers with water soluble monomers for photoresist and lithog. printing applications)

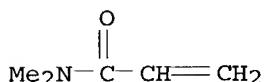
RN 282088-61-3 CAPLUS

CN 2-Propenamide, N,N-dimethyl-, polymer with [(2-propenoxy)methyl]oxirane (9CI) (CA INDEX NAME)

CM 1

CRN 2680-03-7

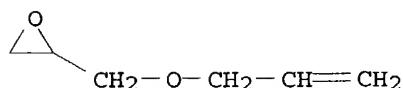
CMF C5 H9 N O



CM 2

CRN 106-92-3

CMF C6 H10 O2

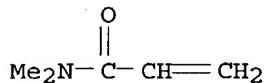


RN 488099-29-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, oxiranylmethyl ester, polymer with N,N-dimethyl-2-propenamide and [(2-propenoxy)methyl]oxirane (9CI) (CA INDEX NAME)

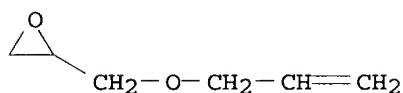
CM 1

CRN 2680-03-7
CMF C5 H9 N O



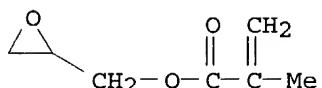
CM 2

CRN 106-92-3
CMF C6 H10 O2



CM 3

CRN 106-91-2
CMF C7 H10 O3



- CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST polymer **photoresist** lithog printing plate application; allyl glycidyl ether copolymer chem amplification **photoresist** lithog printing
IT Sulfonium compounds
RL: PRP (Properties)
(arene, photoacid generators; preparation and characterization of allyl glycidyl ether copolymers with water soluble monomers for **photoresist** and lithog. printing applications)
IT Negative **photoresists**
(chemical amplified; preparation and characterization of allyl glycidyl ether copolymers with water soluble monomers for **photoresist** and lithog. printing applications)
IT Adhesion, physical
(lithog. characterization of allyl glycidyl ether copolymers with water soluble monomers for **photoresist** applications)

- IT Crosslinking
(photochem.; photoimaging of chemical amplification **resists**
based on allyl glycidyl ether copolymers with water soluble monomers)
- IT IR spectra
Lithographic plates
NMR (nuclear magnetic resonance)
Photoimaging materials
Polymerization
(preparation and characterization of allyl glycidyl ether copolymers with
water soluble monomers for **photoresist** and lithog. printing
applications)
- IT Aromatic compounds
RL: PRP (Properties)
(sulfonium, photoacid generators; preparation and characterization of allyl
glycidyl ether copolymers with water soluble monomers for
photoresist and lithog. printing applications)
- IT 75-59-2, Tetramethylammonium hydroxide
RL: NUU (Other use, unclassified); USES (Uses)
(developer; lithog. characterization of allyl glycidyl ether copolymers
with water soluble monomers for **photoresist** applications)
- IT 78-67-1, AIBN
RL: CAT (Catalyst use); USES (Uses)
(preparation and characterization of allyl glycidyl ether copolymers with
water soluble monomers for **photoresist** and lithog. printing
applications)
- IT 110226-18-1P, Allyl glycidyl ether-glycidyl methacrylate-N-vinyl-2-
pyrrolidinone copolymer 282088-61-3P, Allyl glycidyl
ether-N,N-dimethylacrylamide copolymer 488099-29-2P, Allyl
glycidyl ether-N,N-dimethylacrylamide-glycidyl methacrylate copolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(preparation and characterization of allyl glycidyl ether copolymers with
water soluble monomers for **photoresist** and lithog. printing
applications)
- IT 4270-70-6, Triphenylsulfonium chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of mixed arylsulfonium hexafluoroantimonate photoacid generator
for **photoresists** based on allyl glycidyl ether copolymers)
- IT 7440-66-6, Zinc, uses
RL: NUU (Other use, unclassified); USES (Uses)
(substrate; preparation and characterization of allyl glycidyl ether
copolymers with water soluble monomers for **photoresist** and
lithog. printing applications)
- REFERENCE COUNT: 17 THERE ARE 17 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 6 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2002:486496 CAPLUS

DOCUMENT NUMBER: 137:54635

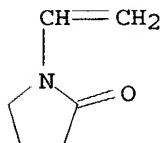
TITLE: 'Method for forming fine **resist** patterns
with excellent dimensional uniformity

INVENTOR(S): Yoshida, Takatsugu; Watanabe, Hisashi

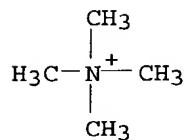
PATENT ASSIGNEE(S): Matsushita Electric Industrial Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002184673	A2	20020628	JP 2000-381895	20001215
PRIORITY APPLN. INFO.:			JP 2000-381895	20001215
AB	The method, useful for semiconductor device fabrication, contains forming a 1st resist (chemical amplified resist , preferably) pattern on a semiconductor substrate, applying a 1st layer on the pattern, heating them, and immersing them in an aqueous solution of tetramethylammonium hydroxide (I) for forming a 2nd resist pattern. The 1st layer may contain aqueous layer-forming components and sulfonate salts. The method containing applying a resist on a semiconductor substrate, heating the resist , applying a 2nd layer on it, heating the layer, exposing them via a mask, heating them, developing them for forming a 1st resist pattern, applying a 3rd layer on the pattern, heating them, and immersing them in an aqueous solution of I for forming a 2nd resist pattern, is also claimed.			
IT	9003-39-8, Poly(vinylpyrrolidone) RL: TEM (Technical or engineered material use); USES (Uses) (3rd layer; photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)			
RN	9003-39-8 CAPLUS			
CN	2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)			
CM	1			
CRN	88-12-0			
CMF	C6 H9 N O			



IT 75-59-2, Tetramethylammonium hydroxide
RL: NUU (Other use, unclassified); USES (Uses)
(photog. for forming fine **resist** patterns by using aqueous tetramethylammonium hydroxide developers)
RN 75-59-2 CAPLUS
CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

- IC ICM H01L021-027
ICS G03F007-039; G03F007-11; G03F007-40
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76
ST resist pattern formation lithog dimensional uniformity;
photoresist development tetramethylammonium hydroxide
semiconductor fabrication; chem amplified resist photolithog sulfonate surfactant
IT Photolithography
 Photoresists
 Semiconductor device fabrication
 (photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)
IT 428864-08-8, TSP 9AEX
RL: TEM (Technical or engineered material use); USES (Uses)
 (2nd or 3rd layer; photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)
IT 9003-39-8, Poly(vinylpyrrolidone)
RL: TEM (Technical or engineered material use); USES (Uses)
 (3rd layer; photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)
IT 75-59-2, Tetramethylammonium hydroxide
RL: NUU (Other use, unclassified); USES (Uses)
 (photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)
IT 438589-81-2, PEK 112A4
RL: TEM (Technical or engineered material use); USES (Uses)
 (photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)
IT 29457-76-9, 1-Octanesulfonic acid, 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8- heptadecafluoro-, compound with 2-aminoethanol (1:1)
RL: TEM (Technical or engineered material use); USES (Uses)
 (surfactant, 3rd layer; photog. for forming fine resist patterns by using aqueous tetramethylammonium hydroxide developers)

L32 ANSWER 7 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2002:332093 CAPLUS

DOCUMENT NUMBER: 136:345862

TITLE: Absorption agents for hygienic materials with a high

INVENTOR(S): swelling capacity reduced tendency to cake
Jonas, Gerd; Mertens, Richard; Frank, Markus
PATENT ASSIGNEE(S): Stockhausen GmbH & Co. Kg, Germany
SOURCE: PCT Int. Appl., 48 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002034384	A2	20020502	WO 2001-EP12315	20011025
WO 2002034384	A3	20020718		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
DE 10052966	A1	20020502	DE 2000-10052966	20001025
AU 2002021743	A5	20020506	AU 2002-21743	20011025
EP 1335756	A2	20030820	EP 2001-988622	20011025
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
BR 2001014916	A	20031223	BR 2001-14916	20011025
JP 2004512165	T2	20040422	JP 2002-537425	20011025
PRIORITY APPLN. INFO.:			DE 2000-10052966 A	20001025
			WO 2001-EP12315 W	20011025

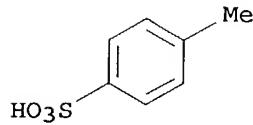
AB The invention relates to absorption agents with a high swelling capacity, which have a reduced tendency to cake in the presence of high air humidity and/or high temps. A swellable polymer is coated with a non-ionic, nitrogen-containing tenside and optionally, a Lewis acid, and caused to react by heating. The superabsorbent polymers are produced and used in hygiene articles and in tech. applications. They further provide unchanged water retention capacities, define retention and retention speed of water or aqueous liq., specifically body fluids. Thus a polymer powder was prepared from acrylic acid, PEG300-diacylate and allyloxypropylmethacrylate acrylic acid ester in sodium hydroxide solution; the powder was mixed with anticaking substances. Properties, e.g. anticaking and absorption capacities were measured.

IT 104-15-4, p-Toluene sulfonic acid, biological studies
52880-34-9

RL: NUU (Other use, unclassified); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(absorption agents with high swelling capacity and with reduced tendency to cake)

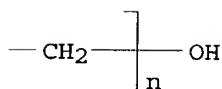
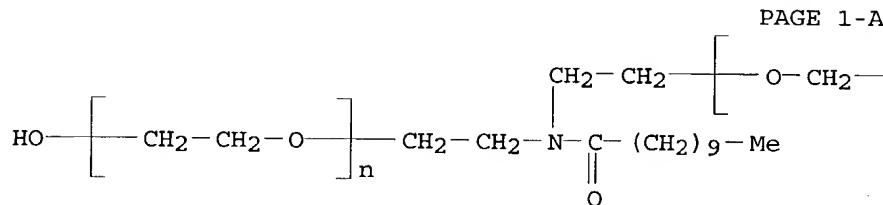
RN 104-15-4 CAPLUS

CN Benzenesulfonic acid, 4-methyl- (9CI) (CA INDEX NAME)



RN 52880-34-9 CAPLUS

CN Poly(oxy-1,2-ethanediyl), α,α' -[[[(1-oxoundecyl)imino]di-2,1-ethanediyl]bis[ω -hydroxy-] (9CI) (CA INDEX NAME)



IC ICM B01J020-00

CC 63-7 (Pharmaceuticals)

Section cross-reference(s): 38

ST absorbent swelling anticaking agent hygienic pad

IT Absorbents

Agglomeration

Agglomeration preventers

Body fluid

Diapers

Heating

Superabsorbents

Surfactants

Swelling, physical

(absorption agents with high swelling capacity and with reduced tendency to cake)

IT Acrylic polymers, biological studies

Lewis acids

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(absorption agents with high swelling capacity and with reduced tendency to cake)

IT Amides, biological studies

RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(coco, N,N-bis(hydroxyethyl), Comperlan COD; absorption agents with high swelling capacity and with reduced tendency to cake)

IT Amides, biological studies
RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(coco, N-(hydroxyethyl), Comperlan 100; absorption agents with high swelling capacity and with reduced tendency to cake)

IT Medical goods
(hygienic materials; absorption agents with high swelling capacity and with reduced tendency to cake)

IT Medical goods
(pads; absorption agents with high swelling capacity and with reduced tendency to cake)

IT Amines, biological studies
RL: NUU (Other use, unclassified); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(tallow alkyl; absorption agents with high swelling capacity and with reduced tendency to cake)

IT Medical goods
(tampons; absorption agents with high swelling capacity and with reduced tendency to cake)

IT 31017-83-1, Marlazin L 10
RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(Marlazin L 10; absorption agents with high swelling capacity and with reduced tendency to cake)

IT 26635-93-8, Marlazin OL 20
RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(Marlazin OL 20; absorption agents with high swelling capacity and with reduced tendency to cake)

IT 26027-37-2, Serdox NXC 3
RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(Serdox NXC 3, Serdox NXC 6, Serdox NXC 14; absorption agents with high swelling capacity and with reduced tendency to cake)

IT 26635-92-7, Stokomin S 10
RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(Stokomin S 10; absorption agents with high swelling capacity and with reduced tendency to cake)

IT 2997-92-4, AAPH 7775-27-1, Sodium peroxydisulfate
RL: CAT (Catalyst use); USES (Uses)
(absorption agents with high swelling capacity and with reduced tendency to cake)

IT 50-21-5, Lactic acid, biological studies 65-85-0, Benzoic acid, biological studies 69-72-7, Salicylic acid, biological studies 77-92-9, Citric acid, biological studies 79-09-4, Propionic acid, biological studies 88-20-0, o-Toluene sulfonic acid 88-99-3, Phthalic acid, biological studies 93-83-4, Oleic acid diethanolamide 98-11-3, Benzene-sulfonic acid, biological studies 104-15-4, p-Toluene sulfonic acid, biological studies 107-92-6, Butyric acid, biological

studies 109-76-2D, 1,3-Propanediamine, tallow derivs. 110-15-6, Succinic acid, biological studies 110-16-7, Maleic acid, biological studies 110-17-8, Fumaric acid, biological studies 111-05-7, Oleic acid isopropanolamide 141-82-2, Malonic acid, biological studies 144-62-7, Oxalic acid, biological studies 526-83-0, Tartaric acid 617-97-0, m-Toluene sulfonic acid 1066-51-9, Aminomethane phosphonic acid 7647-01-0, Hydrogen chloride, biological studies 7664-38-2, Phosphoric acid, biological studies 7664-93-9, Sulfuric acid, biological studies 7697-37-2, Nitric acid, biological studies 10035-10-6, Hydrogen bromide, biological studies 13881-91-9, Aminomethane sulfonic acid 52725-64-1 52880-34-9 56863-02-6, Linolic acid diethanolamide

RL: NUU (Other use, unclassified); THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(absorption agents with high swelling capacity and with reduced tendency to cake)

IT 328061-16-1P 418759-52-1P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); PREP (Preparation); USES (Uses)

(absorption agents with high swelling capacity and with reduced tendency to cake)

IT 120-40-1, Comperlan LD 9003-01-4, Polyacrylic acid

RL: PRP (Properties); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(absorption agents with high swelling capacity and with reduced tendency to cake)

L32 ANSWER 8 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2002:71788 CAPLUS

DOCUMENT NUMBER: 136:139647

TITLE: Multi-layer reaction mixtures and apparatuses for delivering a volatile component via a controlled exothermic reaction

INVENTOR(S): Li, Yu-Jun; Mao, Mark Hsiang-Kuen; Tamura, Haruo; Hu, Hsin-Yuan

PATENT ASSIGNEE(S): The Procter & Gamble Company, USA

SOURCE: PCT Int. Appl., 36 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

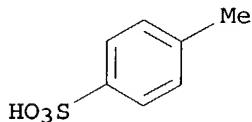
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

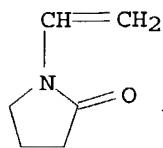
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002005640	A1	20020124	WO 2000-US19081	20000713
W:	AE, AG, AL, AM, AT, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CR, CU, CZ, CZ, DE, DE, DK, DK, DM, DZ, EE, EE, ES, FI, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM,			

TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ,
MD, RU, TJ, TM
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY,
DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ,
CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
EP 1298993 A1 20030409 EP 2000-950328 20000713
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
IE, SI, LT, LV, FI, RO, MK, CY, AL
JP 2004503669 T2 20040205 JP 2002-511590 20000713
US 2003105192 A1 20030605 US 2003-340993 20030113
PRIORITY APPLN. INFO.: WO 2000-US19081 W 20000713
AB Multilayer reaction mixts. that include exothermic generating particles
having a water soluble coating encasing a portion of the particles,
a volatile component and, optionally, a buffer, an aqueous solution or both are
disclosed. At least two layers of the reaction mixture contain exothermic
generating particles and at least one layer of the reaction mixture contains
a portion of the exothermic generating particles suspended in a gel that
includes the water soluble coating. These multilayer reaction
mixts. are especially suited to generate heat in a controllable manner, so that
volatile components can be controllably released to the surrounding
environment. Apparatus and methods using these multilayer reaction mixts. are
also disclosed.
IT 104-15-4, Toluenesulfonic acid, uses 9003-39-8,
Polyvinylpyrrolidone
RL: MOA (Modifier or additive use); USES (Uses)
(multilayer reaction mixts. and apparatuses for delivering volatile
component via controlled exothermic reaction such as air treatment with
perfumes and insecticides)
RN 104-15-4 CAPLUS
CN Benzenesulfonic acid, 4-methyl- (9CI) (CA INDEX NAME)



RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)
CM 1
CRN 88-12-0
CMF C6 H9 N O



IC ICM A01N025-20
ICS A61M011-04; A01G013-06
CC 62-5 (Essential Oils and Cosmetics)
Section cross-reference(s): 59
ST air fragrance insecticide exothermic reaction
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(Cauout; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(Costus; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(Labdanum; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(Salvia; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(Verbena; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Waxes
RL: MOA (Modifier or additive use); USES (Uses)
(ambergris; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(bergamot; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
IT Vinyl compounds, uses
RL: MOA (Modifier or additive use); USES (Uses)
(carboxy-containing, polymers; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction

such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(chamomile, German; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Musks
(civet; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(clove; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(eucalyptus; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Genista
Jasminum
Mimosa
Narcissus
Rose (Rosa)
(exts.; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(lavender; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(lemon; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Acaricides
Air conditioning
Antibacterial agents
Chemiluminescent substances
Citronella (genus)
Deodorants
Disinfectants
Dyes
Exothermic reaction
Fluorescent substances
Fumigants
Insect repellents
Insecticides
Musks

Odor and Odorous substances
Pearlescent pigments
Perfumes
Pesticides
Volatile substances
(multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Acrylic polymers, uses
Albumins, uses
Bentonite, uses
Caseins, uses
Collagens, uses
Gelatins, uses
Hydrides
Hydroxides (inorganic)
Oxides (inorganic), uses
Polymers, uses
Polyoxyalkylenes, uses
RL: MOA (Modifier or additive use); USES (Uses)
(multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Liquids
(oils, castreum; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Resins
RL: MOA (Modifier or additive use); USES (Uses)
(olibanum; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(peppermint; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Vinyl compounds, uses
RL: MOA (Modifier or additive use); USES (Uses)
(polymers; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(rosemary; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(sage, Salvia officinalis; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

- IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(sandalwood; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
- IT Daucus carota
(seed extract; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
- IT Polyphosphoric acids
RL: MOA (Modifier or additive use); USES (Uses)
(sodium salts; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
- IT Essential oils
RL: MOA (Modifier or additive use); USES (Uses)
(sour orange neroli; multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)
- IT 50-21-5, Lactic acid, uses 50-81-7, Ascorbic acid, uses 56-65-5, Adenosinetriphosphate, uses 56-86-0, Glutamic acid, uses 59-67-6, Nicotinic acid, uses 60-12-8, β .-Phenylethyl alcohol 64-18-6, Formic acid, uses 64-19-7, Acetic acid, uses 65-85-0, Benzoic acid, uses 69-72-7, Salicylic acid, uses 76-22-2, Camphor 77-92-9, Citric acid, uses 78-70-6 79-09-4, Propanoic acid, uses 79-14-1, Glycolic acid, uses 80-69-3, Tartronic acid 87-69-4, Tartaric acid, uses 88-99-3, Phthalic acid, uses 89-78-1, Menthol 90-64-2, Mandelic acid 91-20-3D, Naphthalene, derivs. 93-15-2, Methyl eugenol 97-53-0, Eugenol 97-54-1 98-11-3, Benzenesulfonic acid, uses 98-79-3, Pyrrolidone carboxylic acid 98-86-2, Acetophenone, uses 100-21-0, Terephthalic acid, uses 100-51-6, Benzyl alcohol, uses 101-86-0, α .-Hexylcinnamic aldehyde 103-36-6, Ethyl cinnamate 103-54-8, Cinnamyl acetate 103-82-2, Phenylacetic acid, uses 103-95-7, Cyclamen aldehyde 104-15-4, Toluenesulfonic acid, uses 104-46-1, Anethole 104-54-1, Cinnamyl alcohol 104-67-6, γ .-Undecalactone 105-54-4, Ethyl butyrate 106-23-0 106-24-1, Geraniol 107-75-5, Hydroxycitronellal 107-92-6, Butyric acid, uses 109-52-4, Valeric acid, uses 110-15-6, Succinic acid, uses 110-16-7, Maleic acid, uses 110-17-8, Fumaric acid, uses 110-38-3, Ethyl caprate 110-44-1, Sorbic acid 110-94-1, Glutaric acid 111-16-0, Pimelic acid 115-95-7, Linalyl acetate 116-02-9, 3,3,5-Trimethylcyclohexanol 120-72-9, Indole, uses 121-32-4, Ethyl vanillin 121-33-5, Vanillin 121-91-5, Isophthalic acid, uses 122-00-9, p-Methylacetophenone 122-03-2, Cumin aldehyde 122-40-7 122-63-4, Benzyl propionate 123-92-2, Isoamyl acetate 124-04-9, Adipic acid, uses 134-20-3, Methyl anthranilate 140-11-4, Benzyl acetate 141-82-2, Malonic acid, uses 144-62-7, Oxalic acid, uses 149-91-7, Gallic acid, uses 473-81-4, Glyceric acid 487-79-6, Kainic acid 507-70-0, Borneol 526-95-4, Gluconic acid 528-44-9, Trimellitic acid 552-63-6, Tropic acid 600-15-7, α -Hydroxybutyric acid 621-82-9, Cinnamic acid, uses 627-83-8, Ethyleneglycol distearate 1304-56-9, Beryllium oxide, uses 1305-78-8, Calcium oxide, uses 1327-43-1, Aluminum magnesium silicate 1330-43-4,

Sodium tetraborate 1337-83-3, Undecenal 1405-86-3, Glycyrrhizic acid 2466-09-3, Pyrophosphoric acid 5329-14-6, Sulfamic acid 5392-40-5, Citral 6915-15-7, Malic acid 7320-34-5, Potassium pyrophosphate 7429-90-5D, Aluminum, oxides, hydroxides, or hydrides 7439-89-6D, Iron, oxides, hydroxides, or hydrides 7439-93-2D, Lithium, oxides, hydroxides, or hydrides 7439-95-4D, Magnesium, oxides, hydroxides, or hydrides 7440-09-7D, Potassium, oxides, hydroxides, or hydrides 7440-23-5D, Sodium, oxides, hydroxides, or hydrides 7440-41-7D, Beryllium, oxides, hydroxides, or hydrides 7440-50-8D, Copper, oxides, hydroxides, or hydrides 7440-66-6D, Zinc, oxides, hydroxides, or hydrides 7440-70-2D, Calcium, oxides, hydroxides, or hydrides 7487-88-9, Magnesium sulfate, uses 7558-80-7, Sodium dihydrogen phosphate 7601-54-9, Sodium phosphate 7631-86-9, Silica, uses 7631-90-5, Sodium hydrogen sulfite 7664-38-2, Orthophosphoric acid, uses 7722-88-5, Sodium pyrophosphate 7727-15-3, Aluminum bromide 7773-03-7, Potassium hydrogen sulfite 7778-77-0, Potassium dihydrogen phosphate 7784-23-8, Aluminum iodide 7786-30-3, Magnesium chloride, uses 7789-78-8, Calcium hydride 9000-01-5, Gum arabic 9000-07-1, Carrageenan 9000-30-0, Gum guar 9000-36-6, Karaya gum 9000-40-2, Carob-seed gum 9000-65-1, Gum tragacanth 9000-69-5, Pectin 9002-18-0, Agar 9002-89-5, Polyvinyl alcohol 9002-98-6 9003-04-7, Sodium polyacrylate 9003-05-8, Poly acrylamide 9003-09-2, Poly (vinyl methyl ether) 9003-32-1, Poly ethylacrylate 9003-39-8, Polyvinylpyrrolidone 9004-32-4, Sodium carboxymethylcellulose 9004-34-6, Cellulose, uses 9004-54-0, Dextran, uses 9004-57-3, Ethylcellulose 9004-62-0, Hydroxyethylcellulose 9004-64-2, Hydroxypropylcellulose 9004-65-3, Methylhydroxypropylcellulose 9004-67-5, Methylcellulose 9004-70-0, Nitrocellulose 9005-22-5, Sodium cellulose sulfate 9005-25-8, Starch, uses 9005-32-7, Alginic acid 9005-37-2 9005-38-3, Sodium alginate 9011-85-2, Quince seed gum 9014-37-3 9037-55-2, Galactan 9057-02-7, Pullulan 9057-06-1, Carboxymethyl starch 11138-66-2, XanthanGum 12136-45-7, Potassium oxide, uses 12173-47-6, Hectorite 13327-32-7, Beryllium hydroxide 16853-85-3, Lithium aluminum hydride 25763-86-4, Disulfurous acid, monosodium salt 36729-58-5, Decanol 50984-52-6, Anisaldehyde 53563-67-0D, derivs. 57856-81-2, Allylcaprate 61970-00-1, Firefly luciferase 111937-70-3, Hydroxyacrylic acid 141533-39-3 392247-40-4
RL: MOA (Modifier or additive use); USES (Uses)
(multilayer reaction mixts. and apparatuses for delivering volatile component via controlled exothermic reaction such as air treatment with perfumes and insecticides)

REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 9 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2001:597783 CAPLUS
DOCUMENT NUMBER: 135:170788
TITLE: Acrylic enteric coating compositions
INVENTOR(S): Chittamuru, Ramireddy; Reyes, George; Farrell, Thomas P.; Vesey, Charles F.; Mehra, Dev K.; Petereit, Hans-ulrich; Lehmann, Klaus
PATENT ASSIGNEE(S): Bpsi Holdings, Inc., USA; Rohm GmbH Chemische Fabrik

SOURCE: PCT Int. Appl., 29 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2001058429	A1	20010816	WO 2001-US4167	20010209
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG				
US 6420473	B1	20020716	US 2000-501866	200000210
US 2001022972	A1	20010920	US 2001-766859	20010119
EP 1272165	A1	20030108	EP 2001-910485	20010209
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
BR 2001008145	A	20030121	BR 2001-8145	20010209
JP 2003522139	T2	20030722	JP 2001-557540	20010209
NO 2002003784	A	20020902	NO 2002-3784	20020809
PRIORITY APPLN. INFO.:			US 2000-501866	A 200000210
			US 2001-766859	A 20010119
			WO 2001-US4167	W 20010209
AB	A non-toxic, edible, enteric film coating, dry powder composition for use in making an aqueous enteric suspension which may be used in coating pharmaceutical tablets comprises: a) an acrylic resin, said resin comprising i) from 20 to 85 percent by weight of at least one alkyl acrylate or alkyl methacrylate moiety, ii) from 80 to 15 percent by weight of at least one vinyl or vinylidene moiety having a carboxylic acid group capable of salt formation, and iii) from 0 to 30 percent by weight of at least one other vinyl or vinylidene moiety copolymerizable with i) and ii), b) an alkalizing agent capable of reacting with the acrylic resin such that, after reaction, 0.1 to 10 mol percent of the acidic groups in i-a-iii) are present in the salt form, and c) detackifier. An example of the acrylic compound used in coating was Eudragit L100-55.			
IT	1310-58-3, Potassium hydroxide, biological studies 1310-73-2, Sodium hydroxide, biological studies 9003-39-8, Pvp			
	RL: MOA (Modifier or additive use); PEP (Physical, engineering or chemical process); THU (Therapeutic use); BIOL (Biological study); PROC (Process); USES (Uses)			
	(acrylic enteric coating compns.)			
RN	1310-58-3 CAPLUS			
CN	Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)			

K- OH

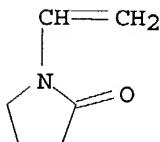
RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na- OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM A61K009-20
ICS A61K009-30; A61K047-06; B05D003-00; C08K005-34; C08K005-10
CC 63-6 (Pharmaceuticals)
ST enteric coating powder suspension acrylic
IT Flours and Meals
 (Amorphophallus rivieri flour; acrylic enteric coating
 compns.)
IT Coating materials
 Dyes
 Pigments, nonbiological
 Plasticizers
 Surfactants
 (acrylic enteric coating compns.)
IT Carbon black, biological studies
 Castor oil
 Kaolin, biological studies
 Polyoxyalkylenes, biological studies
RL: MOA (Modifier or additive use); PEP (Physical, engineering or chemical
process); THU (Therapeutic use); BIOL (Biological study); PROC (Process);
USES (Uses)
 (acrylic enteric coating compns.)
IT Drug delivery systems
 (enteric; acrylic enteric coating compns.)
IT Amorphophallus rivieri
 (flour; acrylic enteric coating compns.)

IT Drug delivery systems
(suspensions; acrylic enteric coating compns.)
IT Drug delivery systems
(tablets; acrylic enteric coating compns.)
IT 56-81-5, Glycerol, biological studies 71-52-3, Bicarbonate, biological studies 77-89-4, Acetyl triethyl citrate 77-93-0, Triethyl citrate 83-88-5, Riboflavin, biological studies 84-66-2, Diethyl phthalate 102-76-1, Glyceryl triacetate 109-43-3, Dibutyl sebacate 151-21-3, Sodium lauryl sulfate, biological studies 458-37-7, Curcumin 506-87-6, Ammonium carbonate 546-93-0, Magnesium carbonate 577-11-7, Dioctyl sodium sulfosuccinate 1066-33-7, Ammonium bicarbonate 1305-62-0, Calcium hydroxide, biological studies 1309-42-8, Magnesium hydroxide 1309-48-4, Magnesium oxide, biological studies 1310-58-3, Potassium hydroxide, biological studies 1310-73-2, Sodium hydroxide, biological studies 1332-37-2, Iron oxide, biological studies 1390-65-4, Carmine 1393-63-1, Annatto 3812-32-6, Carbonate, biological studies 7631-86-9, Silica, biological studies 9000-07-1, Carrageenan 9003-11-6, Oxirane, polymer with methyloxirane 9003-39-8, Pvp 9004-32-4, sodium CM-cellulose 9004-62-0, Hydroxyethyl cellulose 9004-65-3, Hpmc 9005-37-2, Propylene glycol alginate 9005-38-3, Sodium alginate 9005-65-6, polysorbate 80 11138-66-2, Xanthan gum 13463-67-7, Titania, biological studies 14265-44-2, Phosphate, biological studies 14807-96-6, Talc, biological studies 25322-68-3, Peg 31566-31-1, Glycerol monostearate 144892-73-9, Aluminum hydrate
RL: MOA (Modifier or additive use); PEP (Physical, engineering or chemical process); THU (Therapeutic use); BIOL (Biological study); PROC (Process); USES (Uses)
(acrylic enteric coating compns.)
IT 25212-88-8, eudragit L100-55
RL: PEP (Physical, engineering or chemical process); THU (Therapeutic use); BIOL (Biological study); PROC (Process); USES (Uses)
(acrylic enteric coating compns.)

REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 10 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2001:380699 CAPLUS
DOCUMENT NUMBER: 135:6958
TITLE: Composition and process for coating
tin oxide-based transparent conductive film
INVENTOR(S): Niume, Kazuma; Utida, Takasi; Kimura, Masateru
PATENT ASSIGNEE(S): Toyo Gosei Kogyo Co., Ltd., Japan
SOURCE: PCT Int. Appl., 24 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2001036544	A1	20010525	WO 2000-JP8095	20001117

W: CA, KR, US
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
PT, SE, TR

JP 2001210156 A2 20010803 JP 2000-344339 20001110
CA 2360442 AA 20010525 CA 2000-2360442 20001117
EP 1152040 A1 20011107 EP 2000-976299 20001117

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
IE, FI

PRIORITY APPLN. INFO.: JP 1999-326634 A 19991117
JP 2000-344339 A 20001110
WO 2000-JP8095 W 20001117

AB Title composition is prepared by dissolving an aqueous polar polymer [e.g., poly(vinyl alc.)] in a water solution mainly containing tin oxide in the presence

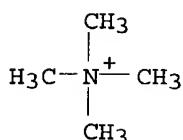
of ≥ 1 compound selected from ammonia and water-soluble amines. Thus, a transparent tin oxide film was obtained by dip-coating a composition at a speed of 5 cm/min on a glass substrate, drying at 100° for 30 min, and baking at 600° for 1 h.

IT 75-59-2, Tetramethylammonium hydroxide

RL: NUU (Other use, unclassified); USES (Uses)
(preparation of composition for coating tin oxide-based transparent conductive film)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

IT 26793-34-0, Polydimethylacrylamide

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(preparation of composition for coating tin oxide-based transparent conductive film)

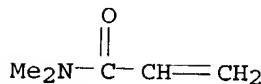
RN 26793-34-0 CAPLUS

CN 2-Propenamide, N,N-dimethyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 2680-03-7

CMF C5 H9 N O



IC ICM C09D001-00
ICS C09D005-24; C03C017-25; C01G019-02; G02F001-1343; H01B013-00;
H01B005-14

CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s) : 74

ST tin oxide ammonia polyvinyl alc transparent conductive film

IT Transparent films
(elec. conductive; preparation of composition for coating tin
oxide-based transparent conductive film)

IT Electric conductors
(films, transparent; preparation of composition for coating
tin oxide-based transparent conductive film)

IT Coating process
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT Amines, uses
RL: NUU (Other use, unclassified); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 18282-10-5P, Tin oxide (SnO₂)
RL: IMF (Industrial manufacture); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 7440-03-1, Niobium, uses 7440-36-0, Antimony, uses 7440-69-9, Bismuth,
uses 7782-41-4, Fluorine, uses 10361-43-0, Bismuth hydroxide
12710-38-2, Niobium hydroxide 152761-81-4, Antimony hydroxide
RL: MOA (Modifier or additive use); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 75-50-3, Trimethylamine, uses 75-59-2, Tetramethylammonium
hydroxide 109-89-7, Diethylamine, uses 121-44-8, Triethylamine, uses
124-40-3, Dimethylamine, uses 7664-41-7, Ammonia, uses
RL: NUU (Other use, unclassified); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 9002-89-5, Polyvinyl alcohol
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or
engineered material use); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 9003-05-8, Polyacrylamide 9004-32-4, CMC 9004-62-0 9004-64-2
26793-34-0, Polydimethylacrylamide 28408-65-3,
Poly(N-vinylacetamide) 28902-82-1, Polyacryloylmorpholine 72018-12-3,
Poly(N-vinylformamide)
RL: POF (Polymer in formulation); TEM (Technical or engineered material

use); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 7787-60-2, Bismuth chloride (BiCl₃) 10025-91-9, Antimony chloride
(SbCl₃) 10026-06-9, Tin chloride (SnCl₄) pentahydrate

RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of composition for coating tin oxide-based
transparent conductive film)

IT 39311-68-7, Stannic acid

RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of composition for coating tin oxide-based
transparent conductive film)

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 11 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2001:360297 CAPLUS

DOCUMENT NUMBER: 134:346483

TITLE: Composition for antireflection
coating on photoresist film

INVENTOR(S): Takano, Yusuke; Tanaka, Hatsuyuki; Lee, Dong Han

PATENT ASSIGNEE(S): Clariant International Ltd., Switz.

SOURCE: PCT Int. Appl., 17 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

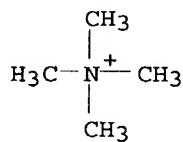
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2001035167	A1	20010517	WO 2000-JP7851	20001108
W: CN, KR, SG, US				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
JP 2001142221	A2	20010525	JP 1999-319888	19991110
EP 1154324	A1	20011114	EP 2000-974831	20001108
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI				
US 6692892	B1	20040217	US 2001-889184	20010710
PRIORITY APPLN. INFO.:			JP 1999-319888	A 19991110
			WO 2000-JP7851	W 20001108
AB	A composition for antireflection coating comprising (a) poly(acrylic acid), (b) poly(vinyl pyrrolidone), (c) C _n F _{2n+1} COOH (n = 3-11), and (d) tetramethylammonium hydroxide is applied to a photoresist film to form an antireflection film. The coated photoresist film is exposed to light and developed to obtain a resist pattern of a satisfactory shape free from T-tops, round tops, etc.			
IT	75-59-2, Tetramethylammonium hydroxide 9003-39-8, Poly(vinyl pyrrolidone)			
	RL: TEM (Technical or engineered material use); USES (Uses)			

(in composition for antireflection coating on
photoresist film)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

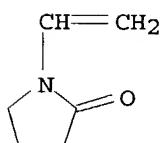
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



IC ICM G03F007-11

ICS C08L033-02

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 42, 73, 76

ST antireflection coating compn photoresist
film photolithog antireflective film

IT Antireflective films
Photolithography
Photoresists

Semiconductor device fabrication

(composition for antireflection coating on
photoresist film)

IT 75-59-2, Tetramethylammonium hydroxide 335-67-1,
Perfluorooctanoic acid 9003-01-4, Poly(acrylic acid) 9003-39-8
, Poly(vinyl pyrrolidone)

RL: TEM (Technical or engineered material use); USES (Uses)
(in composition for antireflection coating on
photoresist film)

REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 12 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2001:338904 CAPLUS
DOCUMENT NUMBER: 134:335353
TITLE: Method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects
INVENTOR(S): De Leeuw, Dagobert M.; Gelinck, Gerwin H.; Matters, Marco
PATENT ASSIGNEE(S): Koninklijke Philips Electronics N.V., Neth.
SOURCE: PCT Int. Appl., 29 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2001033649	A1	20010510	WO 2000-EP10160	20001013
W: JP				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
EP 1145339	A1	20011017	EP 2000-972773	20001013
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2003513475	T2	20030408	JP 2001-535245	20001013
US 6635406	B1	20031021	US 2000-704519	20001102
PRIORITY APPLN. INFO.:			EP 1999-203603 A	19991102
			WO 2000-EP10160 W	20001013

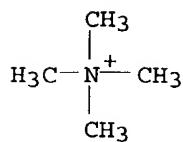
AB The present invention provides a method of photochem. producing a vertical interconnect between a 1st and a 2nd thin-film microelectronic device in a vertical interconnect area which comprises an overlap of a stack of a 1st elec. conducting area, optionally an organic elec. semiconducting area, an organic elec. insulating area comprising adapted photoresist material and a 2nd organic elec. conducting area, in which the organic elec. insulating area is removed within the overlapping area and substituted by an elec. conducting area which is extended from at least the 1st or the 2nd elec. conducting area. The method is useful in the manufacture of electronic devices, preferably integrated circuits, consisting substantially of organic materials.

IT 75-59-2, AZ726MIF

RL: DEV (Device component use); USES (Uses)
(developer; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

IT 9003-39-8, PVP

RL: DEV (Device component use); USES (Uses)
(polymer gate dielec.; method of producing vertical interconnects
between thin film microelectronic devices and products comprising such
vertical interconnects)

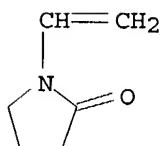
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



IC ICM H01L051-40

ICS H01L051-00; H01L021-768; H01L023-532

CC 76-3 (Electric Phenomena)

Section cross-reference(s): 38

ST vertical interconnect org thin film microelectronic device; photochem
photoresist vertical interconnect thin film microelectronic device

IT Azides

RL: NUU (Other use, unclassified); USES (Uses)
(bis-, photoinitiators; method of producing vertical interconnects
between thin film microelectronic devices and products comprising such
vertical interconnects)

IT Aminoplasts

RL: NUU (Other use, unclassified); USES (Uses)
(crosslinking agent; method of producing vertical interconnects between
thin film microelectronic devices and products comprising such vertical
interconnects)

IT Polyanilines

RL: DEV (Device component use); USES (Uses)
(elec. conductive films; method of producing vertical interconnects
between thin film microelectronic devices and products comprising such

vertical interconnects)

IT Photoresists
UV radiation
(method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Phenolic resins, uses
RL: DEV (Device component use); USES (Uses)
(novolak, polymer gate dielec.; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Dielectric films
Integrated circuits
(organic; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Polymerization catalysts
(photopolymn.; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Phenolic resins, uses
RL: DEV (Device component use); USES (Uses)
(photoresist; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Polyglutarimides
RL: DEV (Device component use); USES (Uses)
(polymer gate dielec.; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Polymers, uses
RL: DEV (Device component use); USES (Uses)
(polythiophenes, semiconductor in FET; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Poly(arylenealkenylenes)
Polyacenes
Polydiacetylenes
PolypHENyLS
RL: DEV (Device component use); USES (Uses)
(semiconductor in FET; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Coating process
(spin; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

IT Glass, uses
Polyamides, uses
Polyimides, uses
RL: DEV (Device component use); USES (Uses)
(substrate; method of producing vertical interconnects between thin

- film microelectronic devices and products comprising such vertical interconnects)
- IT Interconnections (electric)
(vias; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 7440-32-6, Titanium, uses 7440-57-5, Gold, uses
RL: DEV (Device component use); USES (Uses)
(Au/Ti first conductive layer; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 947-19-3, 1-Hydroxycyclohexylphenylketone
RL: NUU (Other use, unclassified); USES (Uses)
(Irgacure 184, photochem. radical initiator; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 59269-51-1, Polyvinyl phenol
RL: DEV (Device component use); USES (Uses)
(conductive materials; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 3089-11-0, Hexamethoxymethylmelamine
RL: NUU (Other use, unclassified); USES (Uses)
(crosslinking agent; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 75-59-2, AZ726MIF
RL: DEV (Device component use); USES (Uses)
(developer; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 108-88-3, Toluene, uses 1330-20-7, Xylene, uses 84540-57-8, Propanol, 1(or 2)-methoxy-, acetate
RL: NUU (Other use, unclassified); USES (Uses)
(developer; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 3144-16-9, Camphorsulfonic acid
RL: NUU (Other use, unclassified); USES (Uses)
(dopants; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 9033-83-4, Polyphenylene 25233-34-5, Polythiophene 96638-49-2, Polyphenylenevinylene 126213-51-2, Poly-3,4-ethylenedioxythiophene
RL: DEV (Device component use); USES (Uses)
(elec. conductive films; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 109211-15-6
RL: RCT (Reactant); RACT (Reactant or reagent)
(for preparation of poly(2,5-thienylene vinylene); method of producing vertical interconnects between thin film microelectronic devices and

products comprising such vertical interconnects)
IT 50851-57-5, Poly(styrenesulfonic acid)
RL: DEV (Device component use); USES (Uses)
(in colloidal solution for conductive layer formation; method of producing
vertical interconnects between thin film microelectronic devices and
products comprising such vertical interconnects)
IT 25155-30-0, Dodecylbenzenesulfonic acid sodium salt 70857-99-7
RL: RCT (Reactant); RACT (Reactant or reagent)
(in colloidal solution for conductive layer formation; method of producing
vertical interconnects between thin film microelectronic devices and
products comprising such vertical interconnects)
IT 26498-02-2, Poly(2,5-thienylene vinylene) 221273-01-4, SU 8 (photoresist)
RL: DEV (Device component use); USES (Uses)
(method of producing vertical interconnects between thin film
microelectronic devices and products comprising such vertical
interconnects)
IT 319482-70-7, XP SU8
RL: NUU (Other use, unclassified); USES (Uses)
(method of producing vertical interconnects between thin film
microelectronic devices and products comprising such vertical
interconnects)
IT 58109-40-3, Diphenyliodonium hexafluoro phosphate
RL: NUU (Other use, unclassified); USES (Uses)
(photoinitiator; method of producing vertical interconnects between
thin film microelectronic devices and products comprising such vertical
interconnects)
IT 37181-39-8, Triflate
RL: NUU (Other use, unclassified); USES (Uses)
(photoinitiators; method of producing vertical interconnects between
thin film microelectronic devices and products comprising such vertical
interconnects)
IT 9003-35-4, CS 100 160903-14-0, OCG-HPR 504 182576-50-7, AZ6612
RL: DEV (Device component use); USES (Uses)
(photoresist; method of producing vertical interconnects
between thin film microelectronic devices and products comprising such
vertical interconnects)
IT 108-78-1, Melamine, uses
RL: DEV (Device component use); USES (Uses)
(polymer gate dielec., polymer of; method of producing vertical
interconnects between thin film microelectronic devices and products
comprising such vertical interconnects)
IT 2628-17-3, p-Hydroxystyrene 9002-89-5 9003-31-0, Polyisoprene
9003-39-8, PVP 49717-87-5, 2-Propenoic acid, ion(1-),
homopolymer, uses
RL: DEV (Device component use); USES (Uses)
(polymer gate dielec.; method of producing vertical interconnects
between thin film microelectronic devices and products comprising such
vertical interconnects)
IT 135-48-8, Pentacene
RL: RCT (Reactant); RACT (Reactant or reagent)
(semiconductive layer of; method of producing vertical interconnects)

- between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 30604-81-0, Polypyrrole 66280-99-7, Poly(thienylene vinylene)
104934-50-1, Poly-3-hexylthiophene
RL: DEV (Device component use); USES (Uses)
(semiconductor in FET; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 108-39-4, m-Cresol, uses
RL: NUU (Other use, unclassified); USES (Uses)
(solvent for doping; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 872-50-4, N-Methylpyrrolidone, uses
RL: NUU (Other use, unclassified); USES (Uses)
(solvent for removing nonconducting area; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)
- IT 7631-86-9, Silica, uses
RL: DEV (Device component use); USES (Uses)
(substrate; method of producing vertical interconnects between thin film microelectronic devices and products comprising such vertical interconnects)

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 13 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2001:98668 CAPLUS
DOCUMENT NUMBER: 134:156352
TITLE: Photoresist pattern formation, semiconductor device, and its manufacture by using the method
INVENTOR(S): Yasuda, Naoki; Toyoshima, Toshiyuki; Ishibashi, Takeo
PATENT ASSIGNEE(S): Mitsubishi Electric Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001033984	A2	20010209	JP 1999-201611	19990715
PRIORITY APPLN. INFO.:			JP 1999-201611	19990715

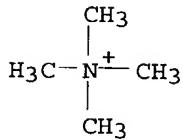
AB The title pattern formation is carried out by the following steps: (1) exposing neg.-working photoresist film to light and developing, (2) forming an organic film on the resulting 1st pattern, and (3) removing the organic film and part of the 1st pattern for formation of a high-precision and very fine 2nd pattern. Preferably, the organic film is a basic polymer, and the film and part of the 1st pattern is removed by using a dissolv. solution. Also claimed are method for manufacture of semiconductor device by using the patterning technique and the resulting

semiconductor device.

IT 75-59-2, Tetramethylammonium hydroxide 9003-39-8,
Polyvinyl pyrrolidone
RL: NUU (Other use, unclassified); USES (Uses)
(fine patterning of neg.-working **photoresist** by formation of
organic film and its removal with dissoln. solution for semiconductor device
fabrication)

RN 75-59-2 CAPLUS

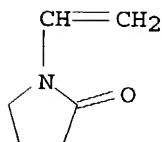
CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM G03F007-40
ICS G03F007-038; H01L021-027
CC 76-3 (Electric Phenomena)
Section cross-reference(s): 74
ST neg **photoresist** pattern formation semiconductor device
fabrication
IT Negative **photoresists**
Semiconductor device fabrication
Semiconductor memory devices
(fine patterning of neg.-working **photoresist** by formation of
organic film and its removal with dissoln. solution for semiconductor device
fabrication)
IT Polyoxyalkylenes, uses
Polyvinyl acetals

RL: NUU (Other use, unclassified); USES (Uses)
(fine patterning of neg.-working **photoresist** by formation of organic film and its removal with dissoln. solution for semiconductor device fabrication)

IT Polyesters, uses
RL: NUU (Other use, unclassified); USES (Uses)
(hydroxy-terminated; fine patterning of neg.-working **photoresist** by formation of organic film and its removal with dissoln. solution for semiconductor device fabrication)

IT 75-59-2, Tetramethylammonium hydroxide 141-43-5,
Monoethanolamine, uses 872-50-4, N-Methylpyrrolidone, uses 9002-89-5,
Polyvinyl alcohol 9002-98-6 9003-01-4, Acrylic acid homopolymer
9003-05-8, Polyacrylamide 9003-19-4, Polyvinyl ether 9003-39-8
, Polyvinyl pyrrolidone 25322-68-3, Polyethylene oxide 26336-38-9,
Polyvinylamine 34540-03-9, Polyacrylimide
RL: NUU (Other use, unclassified); USES (Uses)
(fine patterning of neg.-working **photoresist** by formation of organic film and its removal with dissoln. solution for semiconductor device fabrication)

L32 ANSWER 14 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2000:905577 CAPLUS

DOCUMENT NUMBER: 134:61531

TITLE: Stabilized compositions containing benzimidazole compounds or their alkali metal salts and their enteric coated preparations

INVENTOR(S): Ukai, Koji; Ichikawa, Masaki; Kato, Takashi; Sugatani, Yukiko; Suzuki, Yasuyuki; Aoki, Shigeru; Kato, Akiyoshi; Kawamura, Masao; Fujioka, Masaru

PATENT ASSIGNEE(S): Eisai Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

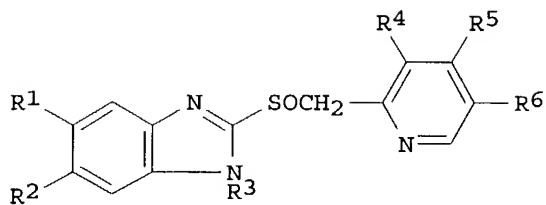
FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000355540	A2	20001226	JP 1999-110462	19990419
PRIORITY APPLN. INFO.:			JP 1998-109288	A 19980420
			JP 1999-105797	A 19990413

OTHER SOURCE(S): MARPAT 134:61531

GI



AB Compns. containing benzimidazole compds. I (R1, R2 = H, OMe, OCHF₂; R3 = H, Na; R4-R6 = H, Me, OMe, methoxypropoxy, trifluoroethoxy) or their alkali metal salts and ≥1 selected from Na₂CO₃, K₂CO₃, NaOH, KOH, aminoalkyl methacrylate copolymer E, arginine aspartate, hydroxypropyl cellulose, and crospovidone are claimed. Also claimed are enteric coated preps. manufactured by coating core tablets comprising the composition with enteric coating optionally via interlayer. I are stabilized in the compns. and preps. and prevented from discoloration. A mixture of rabeprazole Na 10, Na₂CO₃ 10, and mannitol 100 g was granulated while spraying a EtOH solution of 2.5 g hydroxypropyl cellulose, and the granules were mixed with Ca stearate and compressed to give tablets. The tablets were spray-coated with a H₂O/EtOH solution containing

hydroxypropyl Me cellulose phthalate to give enteric-coated tablets.

IT 1310-58-3, Potassium hydroxide, biological studies
1310-73-2, Sodium hydroxide, biological studies 9003-39-8
, Crospovidone

RL: MOA (Modifier or additive use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(stabilized compns. of benzimidazole proton pump inhibitors containing specific stabilizers and enteric-coated tablets thereof)

RN 1310-58-3 CAPLUS

CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K⁻ OH

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na⁻ OH

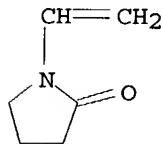
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



- IC ICM A61K031-4439
ICS A61K009-28; A61P001-04; A61P043-00; A61K047-02; A61K047-30;
A61K047-38; C07D401-12
- CC 63-6 (Pharmaceuticals)
- ST benzimidazole proton pump inhibitor stabilization sodium carbonate;
enteric coating benzimidazole proton pump inhibitor stabilizer
- IT Antioxidants
Antiulcer agents
Discoloration prevention agents
Stabilizing agents
(stabilized compns. of benzimidazole proton pump inhibitors containing
specific stabilizers and enteric-coated tablets thereof)
- IT Drug delivery systems
(tablets, enteric-coated; stabilized compns. of
benzimidazole proton pump inhibitors containing specific stabilizers and
enteric-coated tablets thereof)
- IT 7757-83-7, Sodium sulfite
RL: MOA (Modifier or additive use); THU (Therapeutic use); BIOL
(Biological study); USES (Uses)
(antioxidant; stabilized compns. of benzimidazole proton pump
inhibitors containing specific stabilizers and enteric-coated tablets
thereof)
- IT 9004-65-3, Hydroxypropyl methyl cellulose
RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(moisture-proof layer; stabilized compns. of benzimidazole proton pump
inhibitors containing specific stabilizers and enteric-coated tablets
thereof)
- IT 497-19-8, Sodium carbonate, biological studies 584-08-7, Potassium
carbonate 1310-58-3, Potassium hydroxide, biological studies
1310-73-2, Sodium hydroxide, biological studies 7675-83-4,
Arginine aspartate 9003-39-8, Crospovidone 9004-64-2,
Hydroxypropyl cellulose 24938-16-7, Eudragit E
RL: MOA (Modifier or additive use); THU (Therapeutic use); BIOL
(Biological study); USES (Uses)
(stabilized compns. of benzimidazole proton pump inhibitors containing
specific stabilizers and enteric-coated tablets thereof)
- IT 9050-31-1, Hydroxypropyl methyl cellulose phthalate 73590-58-6,
Omeprazole 76633-00-6, Kollidon CL 102625-70-7, Pantoprazole
103577-45-3, Lansoprazole 117976-89-3, Rabeprazole 117976-90-6,
Rabeprazole sodium 185702-31-2, Kollidon CLM
RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(stabilized compns. of benzimidazole proton pump inhibitors containing

specific stabilizers and enteric-coated tablets thereof)

L32 ANSWER 15 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2000:677395 CAPLUS
DOCUMENT NUMBER: 133:256826
TITLE: Coating agents for oral formulations containing HMG-CoA reductase inhibitors
INVENTOR(S): Usui, Fusao; Yada, Shuichi; Kawabata, Kiyoshi
PATENT ASSIGNEE(S): Sankyo Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000264846	A2	20000926	JP 1999-70089	19990316
PRIORITY APPLN. INFO.:			JP 1999-70089	19990316

AB Oral preps. containing HMG-CoA reductase inhibitors, basic compds., and water-soluble polymers, are coated with a composition containing hydroxypropyl Me cellulose acetate succinate and plasticizers, preferably tri-Et citrate. This invention coated preparation allows maintaining of drug blood concentration and prevents isomerization of the drug, e.g. pravastatin. Tablets were formulated containing pravastatin Na, lactose, Crospovidone, Mg aluminate metasilicate, hydroxypropyl cellulose, and Mg stearate. The tablets were coated with a solution containing hydroxypropyl Me cellulose acetate succinate 12.5, tri-Et citrate 2.5, and 70% ethanolic aqueous solution 85 parts.

IT 1310-58-3, Potassium hydroxide, biological studies
1310-73-2, Sodium hydroxide, biological studies 9003-39-8
, PVP

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(coating agents for oral formulations containing HMG-CoA reductase inhibitors)

RN 1310-58-3 CAPLUS
CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K— OH

RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na— OH

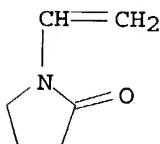
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



IC ICM A61K045-00

ICS A61K009-36; A61K031-00; A61K031-22; A61K047-02; A61K047-38

CC 63-6 (Pharmaceuticals)

ST tablet HMG CoA reductase inhibitor coating; pravastatin tablet coating cellulose ether ester

IT Alkali metal hydroxides

Alkaline earth hydroxides

Alkaline earth oxides

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(coating agents for oral formulations containing HMG-CoA reductase inhibitors)

IT Drug delivery systems

(tablets; coating agents for oral formulations containing HMG-CoA reductase inhibitors)

IT 9028-35-7, HMG-CoA reductase

RL: BSU (Biological study, unclassified); BIOL (Biological study)

(coating agents for oral formulations containing HMG-CoA reductase inhibitors)

IT 77-93-0, Triethyl citrate 1305-62-0, Calcium hydroxide, biological studies 1309-42-8, Magnesium hydroxide 1309-48-4, Magnesia, biological studies 1310-58-3, Potassium hydroxide, biological studies

1310-65-2, Lithium hydroxide 1310-73-2, Sodium hydroxide, biological studies 1336-21-6, Ammonium hydroxide 9003-39-8,

PVP 9004-64-2, Hydroxypropyl cellulose 9004-65-3, Hydroxypropyl methyl cellulose 12511-31-8, Magnesium aluminate metasilicate 21645-51-2,

Aluminum hydroxide, biological studies 71138-97-1, Hydroxypropyl methyl cellulose acetate succinate 74978-16-8, Magaldrate 81093-37-0,

Pravastatin 81131-70-6, Pravastatin sodium

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)

(coating agents for oral formulations containing HMG-CoA reductase inhibitors)

L32 ANSWER 16 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2000:129524 CAPLUS

DOCUMENT NUMBER: 132:286212

TITLE: Cyclized copolymer of methacrylic anhydride and an application to photoresist with photoacid

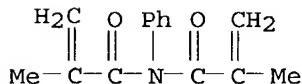
AUTHOR(S) : generator
Takao, Yasuyuki; Miyagawa, Nobukazu; Takahara,
Shigeru; Yamaoka, Tsuguo
CORPORATE SOURCE: Department of Information and Image science, Faculty
of Engineering, Chiba University, Chiba, 263-8522,
Japan
SOURCE: Journal of Photopolymer Science and Technology (1999),
12(5), 769-772
CODEN: JSTEEW; ISSN: 0914-9244
PUBLISHER: Technical Association of Photopolymers, Japan
DOCUMENT TYPE: Journal
LANGUAGE: English

AB The cyclized copolymer of methacrylic anhydride with N-phenyldimethacrylamide and methacrylonitrile was carried out. The polymer consists of six-membered cyclic acid anhydride and five-membered imide ring. The cyclic acid anhydride was hydrolyzed by generated acid catalyst from photoacid generator (PAG). The hydrolyzed copolymer is dissolved in an alkaline solution. The authors applied this copolymer with PAG to photoresist based on the chemical amplified system and obtained good patterns of pos.-tone image.
IT 263896-37-3P, Methacrylic anhydride-methacrylonitrile-N-phenyldimethacrylamide copolymer
RL: PRP (Properties); RCT (Reactant); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(cyclized copolymer of methacrylic anhydride its acid-induced reaction and its application to chemical amplification photoresists)
RN 263896-37-3 CAPLUS
CN 2-Propenoic acid, 2-methyl-, anhydride, polymer with 2-methyl-N-(2-methyl-1-oxo-2-propenyl)-N-phenyl-2-propenamide and 2-methyl-2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 7370-86-7

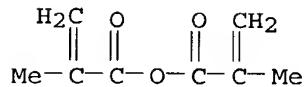
CMF C14 H15 N O2



CM 2

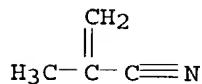
CRN 760-93-0

CMF C8 H10 O3



CM 3

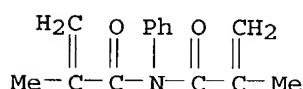
CRN 126-98-7
CMF C4 H5 N



IT 263896-39-5P, Methacrylic anhydride-N-phenyldimethacrylamide copolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (cyclized copolymer. of methacrylic anhydride with N-phenyldimethacrylamide in design of **resists** for photolithog. applications)
RN 263896-39-5 CAPLUS
CN 2-Propenoic acid, 2-methyl-, anhydride, polymer with 2-methyl-N-(2-methyl-1-oxo-2-propenyl)-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

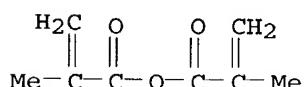
CM 1

CRN 7370-86-7
CMF C14 H15 N O2



CM 2

CRN 760-93-0
CMF C8 H10 O3

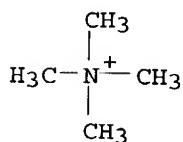


IT 75-59-2, Tetramethylammonium hydroxide

RL: NUU (Other use, unclassified); USES (Uses)
(developer; cyclized copolymer of methacrylic anhydride its
acid-induced reaction and its application to chemical amplification
photoresists)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



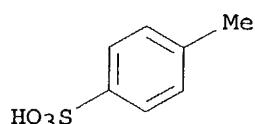
● OH⁻

IT 104-15-4, 4-Toluenesulfonic acid, uses

RL: CAT (Catalyst use); USES (Uses)
(thermal reaction of cyclized copolymer of methacrylic anhydride with
acid catalyst in relation to its application to photoresist
with photoacid generator)

RN 104-15-4 CAPLUS

CN Benzenesulfonic acid, 4-methyl- (9CI) (CA INDEX NAME)



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photoresist photoacid reaction methacrylic anhydride cyclized copolymer

IT Photoresists

(chemical amplification; cyclized copolymer of methacrylic anhydride its acid-induced reaction and its application to photoresist with photoacid generator)

IT IR spectra

(cyclized copolymer of methacrylic anhydride with N-phenyldimethacrylamide in design of resists for photolithog. applications)

IT Polymerization

(cyclized; cyclized copolymer of methacrylic anhydride with N-phenyldimethacrylamide in design of resists for photolithog. applications)

IT 263896-37-3P, Methacrylic anhydride-methacrylonitrile-N-phenyldimethacrylamide copolymer

- RL: PRP (Properties); RCT (Reactant); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(cyclized copolymer of methacrylic anhydride its acid-induced reaction and its application to chemical amplification photoresists)
- IT 66003-76-7, Diphenyliodonium trifluoromethanesulfonate
RL: TEM (Technical or engineered material use); USES (Uses)
(cyclized copolymer of methacrylic anhydride its acid-induced reaction and its application to chemical amplification photoresists)
- IT 263896-39-5P, Methacrylic anhydride-N-phenyldimethacrylamide copolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(cyclized copolymer of methacrylic anhydride with N-phenyldimethacrylamide in design of **resists** for photolithog. applications)
- IT 75-59-2, Tetramethylammonium hydroxide
RL: NUU (Other use, unclassified); USES (Uses)
(developer; cyclized copolymer of methacrylic anhydride its acid-induced reaction and its application to chemical amplification photoresists)
- IT 104-15-4, 4-Toluenesulfonic acid, uses
RL: CAT (Catalyst use); USES (Uses)
(thermal reaction of cyclized copolymer of methacrylic anhydride with acid catalyst in relation to its application to photoresist with photoacid generator)

REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 17 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1999:624727 CAPLUS
DOCUMENT NUMBER: 131:236815
TITLE: Semiconductor device having fine patterns and its fabrication
INVENTOR(S): Saito, Takayuki; Ishibashi, Takeo; Toyoshima, Toshiyuki; Sugino, Kanji
PATENT ASSIGNEE(S): Mitsubishi Denki K. K., Japan; Mitsubishi Electric Corp.
SOURCE: Ger. Offen., 14 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 19857094	A1	19990923	DE 1998-19857094	19981210
DE 19857094	B4	20040325		
TW 449799	B	20010811	TW 1998-87118976	19981117
PRIORITY APPLN. INFO.:			JP 1998-56686	A 19980309
			JP 1998-130052	A 19980513

AB In preparation of a fine **resist** pattern on a semiconductor substrate

which is narrower than the wavelength of the illumination light of a stepper, an acid-catalytically chemical strengthened photoresist is formed, and an organic film which contains an acid or forms an acid on illumination is formed on the substrate, including the resist pattern. The organic film is then heat treated to diffuse the acid. The surface layer of the resist pattern is made soluble in an alkaline developer and then is removed by an alkaline developer. As a result, a fine resist pattern is formed.

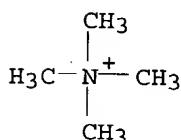
IT 75-59-2, Tetramethylammonium hydroxide 9003-39-8,
Polyvinylpyrrolidone

RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(in fabrication of semiconductor devices having fine patterns)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

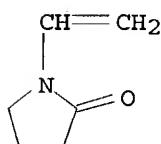
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM H01L021-312

ICS H01L021-31; H01L021-3105; H01L021-768

CC 76-3 (Electric Phenomena)

ST semiconductor device fine pattern manuf

IT Semiconductor device fabrication

(fabrication of semiconductor devices having fine patterns)

IT Semiconductor devices

(having fine patterns)

IT **Photoresists**

(in fabrication of semiconductor devices having fine patterns)

IT Carboxylic acids, processes

Onium compounds

Polymers, processes

Polyvinyl acetals

RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(in fabrication of semiconductor devices having fine patterns)

IT Heat treatment

(of organic films in fabrication of semiconductor devices having fine patterns)

IT 69-72-7, Salicylic acid, processes 75-59-2, Tetramethylammonium

hydroxide 141-43-5, Ethanolamine, processes 1608-42-0 7664-41-7, Ammonia, processes 9002-89-5, Polyvinyl alcohol 9003-01-4, Polyacrylic acid 9003-39-8, Polyvinylpyrrolidone 20680-48-2 25191-25-7, Polyvinyl sulfuric acid 26336-38-9, Polyvinyl amine 30361-82-1 55318-89-3, Diazobenzenesulfonic acid

RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(in fabrication of semiconductor devices having fine patterns)

L32 ANSWER 18 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1999:427455 CAPLUS

DOCUMENT NUMBER: 131:94865

TITLE: Metal thin-film pattern formation by electroless plating of photoresist

INVENTOR(S): Takagi, Yoshihiro; Nagata, Soichiro

PATENT ASSIGNEE(S): Fuji Film Orlean K. K., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 19 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 11186697	A2	19990709	JP 1997-351521	19971219

PRIORITY APPLN. INFO.: JP 1997-351521 19971219

AB The metal thin-film patterns useful as elec. circuits are formed by electroless plating of photoresist patterns formed on a substrate. The electroless plating solution contains a specific reducing agent. The metal thin-film pattern formation is especially suitable for manufacturing

large screen plasma displays.

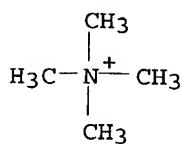
IT 75-59-2, Tetramethylammonium hydroxide 9003-39-8, Poly(vinyl pyrrolidone)

RL: TEM (Technical or engineered material use); USES (Uses)

(in electroless plating solution for metal thin-film pattern formation by electroless plating of photoresist)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

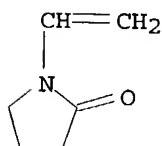
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM H05K003-18

ICS C23C018-16; C23C018-31; G02F001-1343; G03F007-40

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 76

ST metal thin film pattern formation electroless plating **photoresist**
; elec circuit fabrication electroless plating soln

IT Coating process

(electroless; metal thin-film pattern formation by electroless plating
of **photoresist**)

IT Reducing agents

(in electroless plating solution for metal thin-film pattern formation by
electroless plating of **photoresist**)

IT Gelatins, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(in electroless plating solution for metal thin-film pattern formation by
electroless plating of **photoresist**)

IT **Photoresists**

(metal thin-film pattern formation by electroless plating of)

IT Electric circuits

(metal thin-film pattern formation by electroless plating of
photoresist for)

IT Plasma display panels
(metal thin-film pattern formation by electroless plating of photoresist for manufacturing large screen)

IT 60-24-2 62-56-6, Thio urea, uses 75-59-2, Tetramethylammonium hydroxide 96-45-7, Ethylene thiourea 107-15-3, 1,2-Ethanediamine, uses 111-40-0 333-20-0, Potassium thiocyanate 1336-21-6, Ammonium hydroxide 3251-23-8 5244-34-8, 3,6-Dithiaoctan-1,8-diol 7761-88-8, Silver nitrate, uses 7778-53-2, Tripotassium phosphate 7783-18-8, Ammonium thiosulfate 9002-89-5, Poly(vinyl alcohol) 9003-39-8, Poly(vinyl pyrrolidone) 9004-32-4 9017-33-8, Formaldehyde-naphthalenesulfonic acid copolymer 14337-12-3, Chloroaurate 25155-30-0 37353-59-6, Hydroxymethylcellulose
RL: TEM (Technical or engineered material use); USES (Uses)
(in electroless plating solution for metal thin-film pattern formation by electroless plating of photoresist)

IT 7440-22-4P, Silver, preparation 7440-50-8P, Copper, preparation 7440-57-5P, Gold, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(metal thin-film pattern formation by electroless plating of photoresist)

IT 50-00-0, Formaldehyde, uses 50-81-7, L-Ascorbic acid, uses 57-48-7, Fructose, uses 59-23-4, Galactose, uses 80-72-8, Reductic acid 111-30-8, Glutar aldehyde 112-57-2 932-52-5, 5-Aminouracil 9004-53-9, Dextrin 9005-25-8, Starch, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(reducing agent; in electroless plating solution for metal thin-film pattern formation by electroless plating of photoresist)

L32 ANSWER 19 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1998:493162 CAPLUS
DOCUMENT NUMBER: 129:144416
TITLE: Composition for the detection of electrophilic gases and methods of use thereof
INVENTOR(S): Verdicchio, Robert J.; Kaiser, Stewart R.; Walsh, Shawn
PATENT ASSIGNEE(S): R-Tect, Inc., USA
SOURCE: U.S., 4 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 5783110	A	19980721	US 1997-837355	19970417
US 5951909	A	19990914	US 1998-65884	19980424
ZA 9806420	A	19990805	ZA 1998-6420	19980720

PRIORITY APPLN. INFO.: US 1997-837355 A3 19970417
AB There is provided a composition for the detection of an electrophilic gas, such as chlorodifluoromethane or carbon dioxide, which comprises a Lewis base

capable of removing a proton from the gas or reacting therewith in a similar electrophilic manner; a dye capable of visibly indicating a color change on protonation or deprotonation; a solvent for the dye, the base and the gas; and a rheol. modifier capable of producing a non-Newtonian gel of all of these components which is sufficiently translucent to permit visual detection of change of color of the dye and of sufficient pseudoplasticity/thixotropy to provide adhesion to vertical and horizontal surfaces.

IT 1310-73-2, Sodium hydroxide, uses 9003-39-8,
Polyvinylpyrrolidone

RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(gel composition for detection of electrophilic gases and methods of use containing Lewis base, acid-base indicator or dye, solvent and rheol. modifier)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

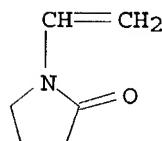
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM B01J013-00

ICS G01M003-20

NCL 252315100

CC 80-3 (Organic Analytical Chemistry)

ST electrophilic gas detection compn

IT Alcohols, uses

Amines, uses

Esters, uses

Ketones, uses

RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(aliphatic; gel composition for detection of electrophilic gases and methods of use containing Lewis base, acid-base indicator or dye, solvent and rheol. modifier)

IT Amines, uses

- RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(alkoxylated; gel composition for detection of electrophilic gases and
methods of use containing Lewis base, acid-base indicator or dye, solvent
and rheol. modifier)
- IT Alcohols, uses
Amines, uses
RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(aralkyl; gel composition for detection of electrophilic gases and methods
of use containing Lewis base, acid-base indicator or dye, solvent and
rheol. modifier)
- IT Acid-base indicators
Electrophiles
Gas analysis
Gums and Mucilages
Rheology
Solvents
(gel composition for detection of electrophilic gases and methods of use
containing Lewis base, acid-base indicator or dye, solvent and rheol.
modifier)
- IT Acrylic polymers, uses
Alkali metal hydroxides
Alkaline earth hydroxides
Alkyd resins
Alkyl halides
Carbonates, uses
Lewis bases
Metal alkoxides
Reagents
RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(gel composition for detection of electrophilic gases and methods of use
containing Lewis base, acid-base indicator or dye, solvent and rheol.
modifier)
- IT Quaternary ammonium compounds, uses
RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(hydroxides; gel composition for detection of electrophilic gases and
methods of use containing Lewis base, acid-base indicator or dye, solvent
and rheol. modifier)
- IT Coating process
(spray; gel composition for detection of electrophilic gases and
methods of use containing Lewis base, acid-base indicator or dye, solvent
and rheol. modifier)
- IT 9003-01-4D, Polyacrylic acid, crosslinked with allyl ethers of
pentaerythritol or sucrose
RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(Carbopol; gel composition for detection of electrophilic gases and methods
of use containing Lewis base, acid-base indicator or dye, solvent and
rheol. modifier)
- IT 9002-88-4, Polyethylene 9004-57-3, Ethylcellulose
RL: ARU (Analytical role, unclassified); ANST (Analytical study)
(coating; gel composition for detection of electrophilic
gases and methods of use containing Lewis base, acid-base indicator or dye,
solvent and rheol. modifier)

IT 75-45-6, Chlorodifluoromethane 124-38-9, Carbon dioxide, analysis
RL: ANT (Analyte); ANST (Analytical study)
(gel composition for detection of electrophilic gases and methods of use containing Lewis base, acid-base indicator or dye, solvent and rheol. modifier)

IT 67-56-1, Methanol, uses 67-64-1, Acetone, uses 67-68-5, Dimethylsulfoxide, uses 109-99-9, Tetrahydrofuran, uses 125-20-2, Thymolphthalein 141-78-6, Ethyl acetate, uses 143-74-8, Phenol red 1310-73-2, Sodium hydroxide, uses 1934-21-0, FD and C Yellow Number 5 2303-01-7, m-Cresol purple 7732-18-5, Water, uses 9002-89-5 9002-89-5D, Polyvinyl alcohol, derivs. 9003-39-8, Polyvinylpyrrolidone 9004-34-6D, Cellulose, hydroxyalkyl derivs., uses 9004-62-0, Hydroxy ethyl cellulose 9005-32-7D, Alginic acid, derivs. 9005-38-3, Sodium alginate
RL: ARG (Analytical reagent use); ANST (Analytical study); USES (Uses)
(gel composition for detection of electrophilic gases and methods of use containing Lewis base, acid-base indicator or dye, solvent and rheol. modifier)

REFERENCE COUNT: 20 THERE ARE 20 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L32 ANSWER 20 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1996:422418 CAPLUS
DOCUMENT NUMBER: 125:67746
TITLE: Enteric film coating compositions
for coating pharmaceutical tablets
INVENTOR(S): Mehra, Dev K.; Ramireddy, Chittamuru; Tang, Li-Juan;
Porter, Stuart C.
PATENT ASSIGNEE(S): Berwind Pharmaceutical Services, Inc., USA; Mehra,
Dev, K.; Ramireddy, Chittamuru; Tang, Li-Juan; Porter,
Stuart, C.
SOURCE: PCT Int. Appl., 62 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9610995	A1	19960418	WO 1995-US12934	19951006
W: AL, AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI, GB, GE, HU, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ				
RW: KE, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG				
US 5733575	A	19980331	US 1994-319987	19941007
TW 397692	B	20000711	TW 1994-83110201	19941104
ZA 9508147	A	19960716	ZA 1995-8147	19950927
AU 9539513	A1	19960502	AU 1995-39513	19951006

AU 684398	B2	19971211		
EP 781125	A1	19970702	EP 1995-937388	19951006
EP 781125	B1	20031210		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LI, LU, NL, PT, SE				
CN 1162917	A	19971022	CN 1995-195513	19951006
JP 10506913	T2	19980707	JP 1995-512671	19951006
HU 77774	A2	19980828	HU 1998-732	19951006
AT 255887	E	20031215	AT 1995-937388	19951006
US 6013282	A	20000111	US 1997-978661	19971126
US 6039976	A	20000321	US 1997-979537	19971126
PRIORITY APPLN. INFO.:				
US 1994-319987 A1 19941007				
WO 1995-US12934 W 19951006				

AB A non-toxic edible enteric film coating dry powder compn for use in making an aqueous enteric coating suspension which may be used in coating pharmaceutical tablets and the like comprises an enteric film forming polymer, a detackifier, a viscosity modifier, and an alkalizing/anti-coagulating agent. Advantageously, the inventive dry powder compns. may include a solid plasticizer, a lubricant, an anti-caking agent, a liquid plasticizer, and a pigment. An enteric film coating composition contained PVAP-T (titanized polyvinyl acetate phthalate) 85.0, talc-400 12, stearic acid 2.60, sodium alginate 1.80, PEG-3350 12.00, Citroflex-2 2.40, sodium bicarbonate 3.00, and Cabosil EH5 1.20%.

IT 1310-58-3, Potassium hydroxide, biological studies
1310-73-2, Sodium hydroxide, biological studies 9003-39-8, Pvp

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(enteric film coating compns. for coating pharmaceutical tablets containing)

RN 1310-58-3 CAPLUS
CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K— OH

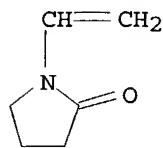
RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na— OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM A61K009-36
CC 63-6 (Pharmaceuticals)
ST enteric film coating pharmaceutical tablet; PVAP talc PEG enteric film coating; stearic acid alginate enteric film coating; bicarbonate PVAP talc enteric film coating
IT Agglomeration preventers
Lubricants
Plasticizers
(enteric film coating compns. for coating pharmaceutical tablets containing)
IT Alkali metal hydroxides
Castor oil
Polymers, biological studies
RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(enteric film coating compns. for coating pharmaceutical tablets containing)
IT Tackifiers
(de-, enteric film coating compns. for coating pharmaceutical tablets containing)
IT Dyes
(lakes, FD&C and D&C; enteric film coating compns. for coating pharmaceutical tablets containing)
IT Pharmaceutical dosage forms
(tablets, enteric film coating compns. for coating pharmaceutical tablets containing)
IT 50-78-2, Aspirin 56-81-5, Glycerol, biological studies 57-11-4, Stearic acid, biological studies 77-89-4, Acetyltriethyl citrate 77-93-0, Triethyl citrate 84-66-2, Diethyl phthalate 102-76-1, Glyceryl triacetate 109-43-3, Dibutyl sebacate 144-55-8, Sodium bicarbonate, biological studies 298-14-6, Potassium bicarbonate 506-87-6, Ammonium carbonate 546-93-0, Magnesium carbonate 1066-33-7, Ammonium bicarbonate 1305-62-0, Calcium hydroxide, biological studies 1309-42-8, Magnesium hydroxide 1309-48-4, Magnesium oxide, biological studies 1310-58-3, Potassium hydroxide, biological studies 1310-73-2, Sodium hydroxide, biological studies 7631-86-9, Silica, biological studies 7632-05-5, Sodium phosphate 9000-07-1, Carrageenan 9003-39-8, Pvp 9004-32-4, Sodium carboxymethyl cellulose 9004-38-0, Cellulose acetate phthalate 9004-62-0, Hydroxyethyl cellulose 9004-65-3, Hydroxypropyl methyl cellulose 9005-38-3, Sodium alginate 11138-66-2, Xanthan gum 13463-67-7, Titanium dioxide, biological studies 14807-96-6, Talc, biological studies 15307-79-6, Sodium diclofenac 16068-46-5, Potassium phosphate 25322-68-3, Peg 53237-50-6D, titanized and jet milled 71138-97-1, Hydroxypropyl methyl cellulose acetate succinate 110268-21-8, Opadry 144892-73-9, Aluminum hydrate

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(enteric film coating compns. for coating
pharmaceutical tablets containing)

IT 37220-17-0, Konjak mannan

RL: THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(flour; enteric film coating compns. for
coating pharmaceutical tablets containing)

L32 ANSWER 21 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1995:813202 CAPLUS

DOCUMENT NUMBER: 123:202394

TITLE: Coating compositions for

water-based ink-printable transparent sheets
INVENTOR(S): Tsuji, Takahiro

PATENT ASSIGNEE(S): Keiwa Shoko Kk, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07186520	A2	19950725	JP 1993-331917	19931227
JP 2547950	B2	19961030		

PRIORITY APPLN. INFO.: JP 1993-331917 19931227

AB The title compns. with good ink receptivity and resistance to yellowing
and opacifying are formulated from water-absorptive polymers (e.g.
polyacrylate), binders [e.g. poly(vinyl alc.)], neutralizing agents (e.g.
amines and alkali metal salts) and/or crosslinking agents (e.g. metal
chelating compds. and epoxy compds.).

IT 9003-39-8, Polyvinylpyrrolidone

RL: TEM (Technical or engineered material use); USES (Uses)
(coating compns. for water-based ink-printable
transparent sheets)

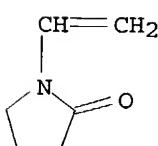
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



IT 1310-58-3, Potassium hydroxide, reactions 1310-73-2,
Sodium hydroxide (Na(OH)), reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(neutralizing agents; **coating compns.** for
water-based ink-printable transparent sheets)
RN 1310-58-3 CAPLUS
CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K—OH

RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

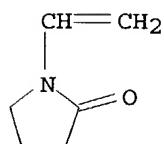
Na—OH

IC ICM B41M005-00
CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74
ST recording overhead transparency waterborne coating; ink receptivity
waterborne **coating compn**; absorbent polymer waterborne
coating; polyvinyl alc binder waterborne coating; amine neutralizing agent
waterborne coating; alkali metal salt waterborne coating; coating
materials
IT Binding materials
Crosslinking agents
(**coating compns.** for water-based ink-printable
transparent sheets)
IT Amines, uses
Polyesters, uses
Polyoxyalkylenes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(**coating compns.** for water-based ink-printable
transparent sheets)
IT Coating materials
(for water-based ink-printable transparent sheets)
IT Recording materials
(overhead transparencies; **coating compns.** for
water-based ink-printable)
IT Polyamines
RL: TEM (Technical or engineered material use); USES (Uses)
(polyethylene-, **coating compns.** for water-based
ink-printable transparent sheets)
IT Alkali metal compounds
RL: TEM (Technical or engineered material use); USES (Uses)
(salts, **coating compns.** for water-based
ink-printable transparent sheets)
IT 9002-89-5, PVA-117 26142-30-3, Polypropylene glycol diglycidyl ether
RL: TEM (Technical or engineered material use); USES (Uses)

- (binder; coating compns. for water-based
ink-printable transparent sheets)
- IT 62-53-3, Benzenamine, reactions 102-71-6, reactions 102-82-9,
Tributylamine 102-86-3, Trihexylamine 107-10-8, Propylamine, reactions
107-11-9, 2-Propen-1-amine 107-15-3, 1,2-Ethanediamine, reactions
109-73-9, Butylamine, reactions 109-76-2, 1,3-Propanediamine 109-89-7,
reactions 110-58-7, Amylamine 110-60-1, Tetramethylenediamine
111-26-2, Hexylamine 111-42-2, reactions 121-44-8, reactions
124-09-4, 1,6-Hexanediamine, reactions 124-22-1, Laurylamine 141-43-5,
reactions 142-84-7, Dipropylamine 462-94-2, Pentamethylenediamine
620-40-6, Tribenzylamine 621-77-2, Tripentylamine 1675-54-3
2425-79-8, 1,4-Butanediol diglycidyl ether 3454-29-3, Trimethylolpropane
triglycidyl ether 6921-29-5, Tripropargylamine 13410-58-7
13963-57-0, Aluminum tris(acetylacetone) 19443-16-4 26403-72-5
RL: RCT (Reactant); RACT (Reactant or reagent)
(coating compns. for water-based ink-printable
transparent sheets)
- IT 9002-98-6 9003-01-4, Acrylic acid polymer 9003-05-8, Acrylamide
polymer 9003-20-7, Poly(vinyl acetate) 9003-39-8,
Polyvinylpyrrolidone 17557-23-2 25322-68-3 25322-69-4
RL: TEM (Technical or engineered material use); USES (Uses)
(coating compns. for water-based ink-printable
transparent sheets)
- IT 100-46-9, Benzylamine, reactions 102-69-2, Tripropylamine 103-83-3,
Dimethylbenzylamine 110-86-1, Pyridine, reactions 110-89-4,
Piperidine, reactions 110-91-8, Morpholine, reactions 1310-58-3
, Potassium hydroxide, reactions 1310-65-2, Lithium hydroxide
1310-73-2, Sodium hydroxide (Na(OH)), reactions 1336-21-6,
Ammonium hydroxide
RL: RCT (Reactant); RACT (Reactant or reagent)
(neutralizing agents; coating compns. for
water-based ink-printable transparent sheets)
- IT 25038-59-9, PET polyester, uses
RL: DEV (Device component use); USES (Uses)
(overhead transparencies; coating compns. for
water-based ink-printable transparent sheets)

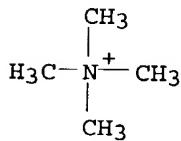
L32 ANSWER 22 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1990:14284 CAPLUS
DOCUMENT NUMBER: 112:14284
TITLE: Resist pattern formation with pretreatment
with aqueous solution
INVENTOR(S): Endo, Masayuki; Sasago, Masaru; Ueno, Atushi; Nomura,
Noboru; Matsuoka, Koji
PATENT ASSIGNEE(S): Matsushita Electric Industrial Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 28 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 314185	A1	19890503	EP 1988-118138	19881031
R: DE, FR, GB				
JP 02084656	A2	19900326	JP 1988-273424	19881028
PRIORITY APPLN. INFO.:			JP 1987-273695	19871029
			JP 1987-284508	19871111
			JP 1988-2870	19880108
			JP 1988-2871	19880108
			JP 1988-2872	19880108
			JP 1988-161652	19880629
AB	<p>A method of forming a fine and well-shaped resist pattern in lithog. fabrication of semiconductor devices comprises coating a resist layer on a substrate, treating the resist layer with an aqueous solution so as to form a surface-treated layer which is difficult to dissolve in an alkaline developer, imagewise exposing the surface-treated resist layer, and subjecting the exposed resist layer to development treatment. The surface treatment enhances the difference in the rate of dissolving in an alkaline developer between exposed and unexposed portions of the resist layer. As a result, a fine and well-shaped pattern with an improved contrast is obtained. The aqueous solution may contain choline or tetramethylammonium hydroxide and a surface-active agent containing F atom or either ether linkage or CO₂H group or SO₃ group or ≥2 of the above-mentioned atom, linkage, and groups. For further improving contrast, the resist layer may be coated with a far-UV-sensitive photofading layer containing a diazo compound or a nitrone compound or a styrylpyridine compound. Heating may be carried out after completion of the aqueous solution treatment.</p>			
IT	9003-39-8, Poly(vinylpyrrolidone)			
RL:	USES (Uses)			
	(photoresist layers coated with, for enhanced contrast in lithog. fabrication of semiconductor devices)			
RN	9003-39-8 CAPLUS			
CN	2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)			
CM	1			
CRN	88-12-0			
CMF	C ₆ H ₉ N O			



IT 75-59-2, Tetramethylammonium hydroxide
 RL: USES (Uses)

(photoresist patterns pretreated with aqueous solns. containing, for
lithog. in fabrication of semiconductor devices)
RN 75-59-2 CAPLUS
CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

IC ICM G03F007-26
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)
Section cross-reference(s): 76
ST resist patterning pretreatment aq soln; semiconductor device
manufg resist patterning
IT Lithography
(photoresist patterning with pretreatment with aqueous solution in,
in fabrication of semiconductor devices)
IT Semiconductor devices
(photoresists patterning with pretreatment with aqueous solution in
fabrication of)
IT Resists
(photo-, patterning of, with pretreatment with aqueous solns.)
IT 7270-63-5, 5-Diazo-Meldrum's acid 9003-39-8,
Poly(vinylpyrrolidone) 50851-57-5
RL: USES (Uses)
(photoresist layers coated with, for enhanced contrast in
lithog. fabrication of semiconductor devices)
IT 62-49-7, Choline 75-59-2, Tetramethylammonium hydroxide
77-98-5, Tetraethylammonium hydroxide
RL: USES (Uses)
(photoresist patterns pretreated with aqueous solns. containing, for
lithog. in fabrication of semiconductor devices)

L32 ANSWER 23 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1989:415210 CAPLUS
DOCUMENT NUMBER: 111:15210
TITLE: Synthesis of new metal-free diazonium salts and their
applications to microlithography
AUTHOR(S): Uchino, Shouichi; Hashimoto, Michiaki; Iwayanagi,
Takao
CORPORATE SOURCE: Cent. Res. Lab., Hitachi Ltd., Kokubunji, 185, Japan
SOURCE: Polymeric Materials Science and Engineering (1989),
60, 255-9

CODEN: PMSEDG; ISSN: 0743-0515

DOCUMENT TYPE:

Journal

LANGUAGE:

English

AB Trifluoromethanesulfonates of 4-diazo-N,N-dimethylaniline and 4-diazoanisole were synthesized and applied not only to the contrast enhanced lithog. (CEL) dyes and neg. working sensitizers but also to photoacid generators for chemical amplification **resist** systems. A CEL layer consisting of 4-diazo-N,N-dimethylaniline trifluoromethanesulfonate (D1) and poly(N-vinylpyrrolidone) had good optical characteristics for i-line exposure and enabled 0.4- μm L&S pos. **resists** patterns. D1 is also a useful material for the neg. working sensitizer of phenolic resins. 4-Diazoanisole trifluoromethanesulfonate can be used as a photoacid generator for an acid-catalyzed close-linking type **resist** system which works in the mid-UV region. Submicron **resist** patterns were resolved using this highly sensitive **resist** system.

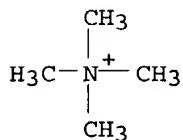
IT 75-59-2, Tetramethylammonium hydroxide

RL: USES (Uses)

(developer, for microlithog. **photoresist** containing metal-free diazonium salt and poly(vinylpyrrolidone))

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

IT 9003-39-8, Polyvinylpyrrolidone

RL: USES (Uses)

(microlithog. **photoresist** from metal-free diazonium salt and)

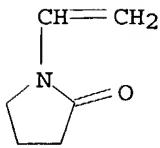
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76
ST microlithog diazonium salt prepn photoresist
IT Diazonium compounds
RL: PREP (Preparation)
(metal-free, preparation for microlithog. photoresists)
IT Resists
(photo-, diazonium salt synthesis for, for microlithog.)
IT 64-17-5, Ethanol, uses and miscellaneous 75-59-2,
Tetramethylammonium hydroxide 78-93-3, Methylethyl ketone, uses and
miscellaneous
RL: USES (Uses)
(developer, for microlithog. photoresist containing metal-free
diazonium salt and poly(vinylpyrrolidone))
IT 121028-48-6
RL: USES (Uses)
(microlithog. photoresist composition containing)
IT 9074-30-0, GE75108 24979-70-2, Poly(4-hydroxystyrene) 25067-05-4,
Polyglycidyl methacrylate
RL: USES (Uses)
(microlithog. photoresist composition containing diazonium salt and)
IT 9003-39-8, Polyvinylpyrrolidone
RL: USES (Uses)
(microlithog. photoresist from metal-free diazonium salt and)
IT 82802-22-0P
RL: PREP (Preparation)
(preparation of, for microlithog. photoresists)
IT 99-98-9, N,N-Dimethyl-p-phenylenediamine 1493-13-6,
Trifluoromethanesulfonic acid
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, in preparation of metal-free diazonium salt for microlithog.
photoresist)

L32 ANSWER 24 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1988:201301 CAPLUS
DOCUMENT NUMBER: 108:201301
TITLE: A body-fluid assay stick with an ink composition
INVENTOR(S): Sakota, Kazuyuki
PATENT ASSIGNEE(S): Dai Nippon Printing Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 62263466	A2	19871116	JP 1986-107872	19860512
JP 07062680	B4	19950705		

PRIORITY APPLN. INFO.: JP 1986-107872 19860512

AB A body fluid assay stick comprises a support coated with an ink composition of reagents dispersed or dissolved in a solvent capable of swelling the support. A stick for determining pH of a urine sample was composed

of a polystyrene sheet coated with a composition containing methyl red Na salt 0.070, bromothymol blue 1.0, dodecyltrimethylammonium chloride 1.0, NaOH 0.088, Kollidon 90 13.2, S-Lec BX-1 1.54, Avicel SF 174, and Bu Cellosolve 257 parts by weight

IT 1310-73-2, Sodium hydroxide, biological studies 9003-39-8

RL: ANST (Analytical study)
(ink compns. containing, for pH determination)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

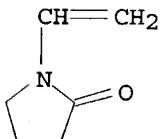
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM G01N033-52

ICS G01N031-22

CC 9-1 (Biochemical Methods)

ST nonaq solvent body fluid assay; styrene polymer body fluid assay; glucose detn body fluid; protein detn body fluid; pH detn body fluid

IT Proteins, analysis

RL: ANT (Analyte); ANST (Analytical study)
(determination of, in body fluid, test sticks for)

IT Albumins, analysis

RL: ANT (Analyte); ANST (Analytical study)

(determination of, in urine, ink compns. for)
IT Body fluid
(glucose and protein and pH determination in, test sticks for)
IT Guaiacum (resin)
(glucose determination with compns. containing)
IT Solvents
(nonaq., body fluid assay compns. containing)
IT Urine analysis
(pH determination in, ink compns. for)
IT Vinyl acetal polymers
RL: ANST (Analytical study)
(butyral, ink compns. containing, for pH determination)
IT 9003-53-6, Polystyrene
RL: ANST (Analytical study)
(body fluid test element with support of)
IT 50-99-7, D-Glucose, analysis
RL: ANT (Analyte); ANST (Analytical study)
(determination of, in body fluid, test stick for)
IT 9003-99-0, Peroxidase 25395-66-8, L-Ascorbyl stearate 9001-37-0,
Glucose oxidase
RL: ANST (Analytical study)
(glucose determination with compns. containing)
IT 76-59-5, Bromothymol blue 111-76-2, Butyl cellosolve 112-00-5,
Dodecyltrimethylammonium chloride 845-10-3, Methyl red sodium salt
1310-73-2, Sodium hydroxide, biological studies 9003-39-8
9004-34-6, Avicel SF, biological studies
RL: ANST (Analytical study)
(ink compns. containing, for pH determination)
IT 68-04-2, Sodium citrate 71-41-0, Amyl alcohol, biological studies
112-07-2, Butyl cellosolve acetate 1338-39-2, Span 20 4430-25-5
9004-32-4 9050-04-8, Carboxymethylcellulose calcium salt 54578-89-1
77-92-9, Citric acid, biological studies
RL: ANST (Analytical study)
(protein determination with compns. containing)

L32 ANSWER 25 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1988:201300 CAPLUS
DOCUMENT NUMBER: 108:201300
TITLE: A body fluid assay stick for glucose detection and
protein detection and/or pH determination, and a
method for manufacturing the stick
INVENTOR(S): Sakota, Kazuyuki
PATENT ASSIGNEE(S): Dai Nippon Printing Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 62263469 A2 19871116 JP 1986-107871 19860512
PRIORITY APPLN. INFO.: JP 1986-107871 19860512

AB A body fluid assay stick is composed of the following regions: (1) a 1st region coated with a glucose-determination ink composition of a nonaq. solvent containing glucose oxidase, peroxidase, nonoxidizing indicator, sensitivity-regulating agent, stabilizer, pH buffer agent, binder, and H₂O-absorbing powders; and (2) 1st, 2nd, and/or 3rd regions coated with a 2nd protein-determination ink composition of a solvent containing a protein-error indicator, pH buffer agent, protein-adsorbing ion exchanger, shape-retaining agent, binder, and H₂O-absorbing powders and/or a 3rd pH-determination ink composition of a solvent containing a pH indicator, quaternary ammonium or amine salt, basic material, binder, and H₂O-absorbing powders. A method for manufacturing the stick involves preparing the 2nd and/or 3rd regions on the support and then preparing the 1st region. A stick for urine anal. was prepared by successively printing a pH-determination ink composition containing NaOH, methyl red, bromothymol blue, dodecyltrimethylammonium chloride, Kollidon 90, S-Lec BX-1, Avicel SF, and Bu Cellosolve, a protein-determination ink composition containing tetrabromophenol blue, citric acid, Na citrate, Span 20, CM-32, CM-cellulose Ca salt, amyl ester of Gantrez AN-169, Avicel SF, amyl alc., and Bu Cellosolve acetate, and a glucose-determination ink composition containing glucose oxidase, peroxidase, guaiacum resin, Span 20, L-ascorbyl stearate, citric acid, Na citrate, Kollidon 90, S-Lec BX-1, Avicel SF, amyl alc., and Bu Cellosolve acetate.

IT 1310-73-2, Sodium hydroxide, biological studies 9003-39-8
RL: ANST (Analytical study)
(ink compns. containing, for urine anal.)

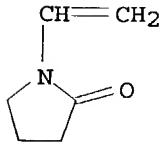
RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C₆ H₉ N O



IC ICM G01N033-66
CC 9-1 (Biochemical Methods)
ST body fluid analysis stick; glucose detn body fluid stick; protein detn
body fluid stick; pH detn body fluid stick; urine analysis glucose protein
pH
IT Body fluid
(anal. of, test sticks for)
IT Proteins, analysis
RL: ANT (Analyte); ANST (Analytical study)
(determination of, in body fluid, test stick for)
IT Albumins, analysis
RL: ANT (Analyte); ANST (Analytical study)
(determination of, in urine, test sticks for)
IT Urine analysis
(glucose and albumin and pH determination in, test sticks for)
IT Alkali metal hydroxides
RL: ANST (Analytical study)
(glucose determination in body fluid with ink composition containing)
IT Guaiacum (resin)
(glucose determination in body fluid with ink compns. containing)
IT Vinyl acetal polymers
RL: ANST (Analytical study)
(butyral, ink compns. containing, for urine anal.)
IT 50-99-7, Glucose, analysis
RL: ANT (Analyte); ANST (Analytical study)
(determination of, in body fluid, test stick for)
IT 492-61-5
RL: ANT (Analyte); ANST (Analytical study)
(determination of, in urine, test stick for)
IT 50-81-7D, Ascorbic acid, esters
RL: ANST (Analytical study)
(glucose determination in body fluid with ink composition containing)
IT 68-04-2, Sodium citrate 71-41-0, Amyl alcohol, biological studies
76-59-5, Bromothymol blue 77-92-9, Citric acid, biological studies
111-76-2, Butyl Cellosolve 112-00-5, Dodecyltrimethylammonium chloride
112-07-2, Butyl Cellosolve acetate 493-52-7, Methyl red
1310-73-2, Sodium hydroxide, biological studies 1338-39-2, Span
20 4430-25-5, Tetrabromophenol blue 9001-37-0, Glucose oxidase
9003-39-8 9003-99-0, Peroxidase 9004-32-4 9004-34-6, Avicel
SF, biological studies 9050-04-8, Carboxymethylcellulose calcium salt
25395-66-8, Ascorbyl stearate 54578-89-1
RL: ANST (Analytical study)
(ink compns. containing, for urine anal.)

L32 ANSWER 26 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1988:183287 CAPLUS
DOCUMENT NUMBER: 108:183287
TITLE: A pH determination ink composition containing a quaternary ammonium or amine salt and basic substance and a test stick for pH determination
INVENTOR(S): Sakota, Kazuyuki
PATENT ASSIGNEE(S): Dai Nippon Printing Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 62261060	A2	19871113	JP 1986-103577	19860506
PRIORITY APPLN. INFO.:			JP 1986-103577	19860506

AB An ink composition for pH determination is composed of a solvent containing a dispersed or dissolved reagent composition of a pH indicator, quaternary ammonium or amine salt, basic substance, binder, and H₂O-absorbing powders. A test stick is composed of a support coated with the above ink composition. An ink composition was prepared by adding BuOH 5 containing NaOH 0.088 parts by weight to a blend containing methyl red Na salt 0.070, bromothymol blue 1.0, dodecytrimethylammonium chloride 1.0, Kollidon 90 13.2, S-Lec BX-1, 1.54, Avicel SF 174, and Bu Cellosolve 257 parts by weight. A stick coated with the above composition showed a bright color when used for a urine sample.

IT 1310-73-2, Sodium hydroxide, biological studies 9003-39-8
RL: BIOL (Biological study)
(pH determination with ink compns. containing)

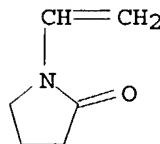
RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC ICM G01N031-22
 ICS G01N033-52; G01N033-84
 CC 9-1 (Biochemical Methods)
 ST alkali metal hydroxide pH detn; urine pH detn ink compn
 IT Acid-base equilibrium
 (determination of, ink composition and test stick for)
 IT Alkali metal hydroxides
 Quaternary ammonium compounds, uses and miscellaneous
 RL: ANST (Analytical study)
 (ink compns. containing, for pH determination)
 IT Urine analysis
 (pH determination in, ink compns. and test sticks for)
 IT Vinyl acetal polymers
 RL: ANST (Analytical study)
 (butyral, pH determination with ink compns. containing)
 IT Amines, compounds
 RL: ANST (Analytical study)
 (salts, ink compns. containing, for pH determination)
 IT 71-36-3, Butanol, biological studies 76-59-5, Bromothymol blue
 111-76-2, Butyl Cellosolve 112-00-5, Dodecyltrimethylammonium chloride
 493-52-7, Methyl red 845-10-3, Methyl red sodium salt 1310-73-2
 , Sodium hydroxide, biological studies 9003-39-8 9004-34-6,
 Avicel SF, biological studies
 RL: BIOL (Biological study)
 (pH determination with ink compns. containing)

L32 ANSWER 27 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
 ACCESSION NUMBER: 1987:536389 CAPLUS
 DOCUMENT NUMBER: 107:136389
 TITLE: Drain cleaner
 INVENTOR(S): Taylor, Roy M., Jr.; Klemm, Steven R.
 PATENT ASSIGNEE(S): Amway Corp., USA
 SOURCE: U.S., 8 pp.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 4664836	A	19870512	US 1985-777409	19850918
PRIORITY APPLN. INFO.:			US 1985-777409	19850918
AB A drain-cleaning composition contains ≥40% free-flowing,				

coated alkali metal hydroxide and 5-20% mixture of hypochlorite generator and peroxide generator. During use, the composition produces free hypochlorite ions for dissolving hair and other protein-based clogs. The coated alkali metal hydroxide does not react with other components of the composition before the mixture is added to water. A drain cleaner comprised 74.7% coated caustic (NaOH) 90.88, phthalocyanine blue 0.12, and C12-14 fatty acid monoethanolamide coating 9.00%, 11.0% effervescent system (citric acid 31.00, NaHCO₃ 49.00, and CaSO₄ 20.00%), 6.2% peroxide source (Na percarbonate 80.00, Na₂CO₃ 12.00, water 1.00, and 40% Na silicate solution as agglomerating agent 10.00%), 8.0% hypochlorite generator (Na dichloroisocyanurate dihydrate), and 0.01 mineral oil (dust inhibitor). The cleaner was effective on drain clogs based on grease, hair, and/or soap.

IT 1310-73-2, Sodium hydroxide, uses and miscellaneous
RL: USES (Uses)

(drain cleaners containing coated particles of, stable)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

IT 9003-39-8, Vinyl pyrrolidone polymer
RL: USES (Uses)

(sodium hydroxide encapsulated by, for drain cleaner)

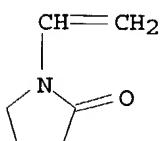
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM C11D007-06

ICS C11D007-54; C11D017-06; B08B009-02

NCL 252091000

CC 46-6 (Surface Active Agents and Detergents)

ST alkali drain cleaner; hypochlorite drain cleaner; peroxide drain cleaner; hair dissolver drain cleaner; drain cleaner hair grease; percarbonate granulation drain cleaner; amide encapsulation alkali cleaner; encapsulation alkali drain cleaner; coating alkali particle cleaner; effervescence alkali drain cleaner; dichloroisocyanurate drain cleaner; silicate granulation percarbonate cleaner

IT Detergents
(drain cleaner, alkali-hypochlorite-peroxide, stable, hair-dissolving)

IT Encapsulation
(of alkali metal hydroxide particles, for stable drain cleaner)

IT Agglomeration
(of sodium percarbonate powder, for drain cleaner)

IT Granulation
(of sodium percarbonate, for stable drain cleaner)

IT Amides, compounds
RL: USES (Uses)
(C12-14, N-(hydroxyethyl), sodium hydroxide particles coated by, drain cleaners containing, stable)

IT 1310-73-2, Sodium hydroxide, uses and miscellaneous
RL: USES (Uses)
(drain cleaners containing coated particles of, stable)

IT 10058-23-8 11138-47-9, Sodium perborate
RL: USES (Uses)
(drain cleaners containing hypochlorite and, stable, hair-dissolving)

IT 2893-78-9
RL: USES (Uses)
(drain cleaners containing peroxide and, stable, hair-dissolving)

IT 15630-89-4, Sodium percarbonate
RL: USES (Uses)
(drain cleaners containing sodium dichloroisocyanurate and, stable, hair-dissolving)

IT 497-19-8, Disodium carbonate, uses and miscellaneous
RL: USES (Uses)
(drain cleaners containing, stable, hair-dissolving)

IT 77-92-9, Citric acid, uses and miscellaneous 87-69-4, Tartaric acid, uses and miscellaneous 110-15-6, Succinic acid, uses and miscellaneous 110-17-8, Fumaric acid, uses and miscellaneous 124-04-9, Adipic acid, uses and miscellaneous 144-55-8, Sodium bicarbonate, uses and miscellaneous 298-14-6, Potassium bicarbonate 533-96-0, Sodium sesquicarbonate 584-08-7, Dipotassium carbonate 6915-15-7, Malic acid 11113-50-1, Boric acid
RL: USES (Uses)
(effervescent system containing, for drain cleaner)

IT 1344-09-8, Sodium silicate
RL: USES (Uses)
(granulating agents, for sodium percarbonate in drain cleaner)

IT 57-55-6, Propylene glycol, uses and miscellaneous
RL: MOA (Modifier or additive use); USES (Uses)
(plasticizers, for Et cellulose coating on sodium hydroxide particles)

IT 141-43-5D, Ethanolamine, amides with fatty acids 9003-01-4, Acrylic acid polymer 9003-09-2, Methyl vinyl ether polymer 9003-11-6, Ethylene oxide-propylene oxide copolymer 9003-39-8, Vinyl pyrrolidone polymer 9004-38-0 9004-57-3, Ethyl cellulose 9006-26-2, Ethylene-maleic anhydride copolymer 9011-13-6 9011-16-9, Maleic anhydride-methyl vinyl ether copolymer 25086-89-9, Vinyl acetate-vinyl pyrrolidone copolymer 25087-26-7, Methacrylic acid polymer 25322-68-3, Polyethylene glycol
RL: USES (Uses)

(sodium hydroxide encapsulated by, for drain cleaner)

L32 ANSWER 28 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1987:468197 CAPLUS
DOCUMENT NUMBER: 107:68197
TITLE: Developers for positive-working photoresists
INVENTOR(S): Tanaka, Hatsuyuki; Asaumi, Shingo
PATENT ASSIGNEE(S): Tokyo Ohka Kogyo Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 62032451	A2	19870212	JP 1985-171833	19850806
US 4784937	A	19881115	US 1986-892646	19860804
PRIORITY APPLN. INFO.:			JP 1985-171833	19850806
			JP 1985-171834	19850806

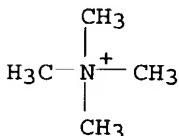
AB The title developers, containing metal ion-free organic bases and 50-500 ppm F-containing nonionic surfactants, are suitable for pos.-working photoresists containing quinone diazides and show reduced temperature-dependence during development. An exposed pos.-working photoresist produced uniform patterns at 15-40° in 30 s when developed with an aqueous solution containing 2.38% tetramethylammonium hydroxide and 500 ppm F₃C(CF₂)₇(CH₂CH₂O)₁₀H.

IT 75-59-2, Tetramethylammonium hydroxide

RL: USES (Uses)
(developer containing, for pos.-working photoresist)

RN 75-59-2 CAPLUS

CN Methanaminium, N,N,N-trimethyl-, hydroxide (9CI) (CA INDEX NAME)



● OH⁻

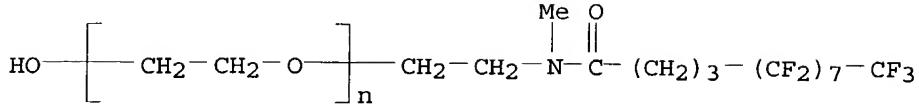
IT 109636-64-8
RL: USES (Uses)

(surfactants, developer containing, for pos.-working photoresist)

RN 109636-64-8 CAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[2-[(5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heptadecafluoro-1-oxododecyl)methylamino]ethyl]-ω-hydroxy-

(9CI) (CA INDEX NAME)



IC ICM G03C005-24
 ICS G03C001-72; G03F007-00; G03F007-08
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 ST photoresist pos developer org base; fluorine nonionic surfactant tetramethylammonium hydroxide; choline tetramethylammonium hydroxide developer photoresist
 IT Resists
 (photo-, pos.-working, developer for, containing fluoro compound surfactant)
 IT 62-49-7 75-59-2, Tetramethylammonium hydroxide
 RL: USES (Uses)
 (developer containing, for pos.-working photoresist)
 IT 29117-08-6 58228-15-2 109636-63-7 109636-64-8
 RL: USES (Uses)
 (surfactants, developer containing, for pos.-working photoresist)

L32 ANSWER 29 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1987:166250 CAPLUS
 DOCUMENT NUMBER: 106:166250
 TITLE: Ink-jet recording system
 INVENTOR(S): Sakaki, Mamoru; Arai, Ryuichi
 PATENT ASSIGNEE(S): Canon K. K., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61199979	A2	19860904	JP 1985-41302	19850304
PRIORITY APPLN. INFO.:			JP 1985-41302	19850304

AB The ink receptor layer of the title system is composed of complexes of a polyalc. with boric acid or a borate and the ink contains 20-90% H₂O. The receptor sheet is noncurling, nonsticking, and retains high ink acceptability at high temperature. The obtained copies are resistant to water and humidity and are storage stable. Thus, A PET film was coated with a composition containing PVA-217, boric acid, and NaOH to form a 100-μ colorless, transparent layer. After ink-jet printing, the image was set for 5 min, to give dot d. 1.1. The image was suitable as transparency for overhead projector. No trouble was experienced in the transport of the material within the recording system and the fingerprints

on the material surface were easily wiped off. A control material without boric acid and NaOH showed good printability, but produced difficulty in mech. transport and was permanently smudged by fingerprints.

IT 1310-73-2, Sodium hydroxide, uses and miscellaneous

RL: USES (Uses)

(ink-jet printing material with receptor sheet containing polyalc. and boric acid and)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na-OH

IT 9003-39-8, Poly(vinylpyrrolidone)

RL: USES (Uses)

(ink-jet printing with receptor layer containing boric acid and)

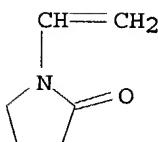
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C6 H9 N O



IC ICM B41M005-00

ICS B41J003-04

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST polyalc borate ink jet receptor; projector transparency ink jet printing

IT Projection slides

(ink-jet printing material for, receptor sheet containing polyalc. and boric acid for)

IT Projection slides

(color, ink-jet printing material for, receptor sheet containing polyalc. and boric acid for)

IT Printing, nonimpact

(ink-jet, with receptor layer containing polyalc. and boric acid)

IT Audio-visual aids

(projection slides, ink-jet printing material for, receptor sheet containing polyalc. and boric acid for)

IT 69-65-8, D-Mannitol 107721-24-4

RL: USES (Uses)

(ink-jet material with receptor sheet containing boric acid and)

IT 1303-96-4, Borax 10043-35-3, Boric acid, uses and miscellaneous
RL: USES (Uses)
(ink-jet printing material with receptor sheet containing polyalc. and)

IT 1310-73-2, Sodium hydroxide, uses and miscellaneous
RL: USES (Uses)
(ink-jet printing material with receptor sheet containing polyalc. and boric acid and)

IT 9002-89-5, Poly(vinylalcohol) 9003-39-8, Poly(vinylpyrrolidone)
9004-62-0, Hydroxyethyl cellulose
RL: USES (Uses)
(ink-jet printing with receptor layer containing boric acid and)

L32 ANSWER 30 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1986:505709 CAPLUS
DOCUMENT NUMBER: 105:105709
TITLE: Processing photosensitive silver halide color photographic material
INVENTOR(S): Koboshi, Shigeharu; Kobayashi, Kazuhiro; Kuse, Satoru
PATENT ASSIGNEE(S): Konishiroku Photo Industry Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 69 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 175153	A2	19860326	EP 1985-110372	19850819
EP 175153	A3	19881117		
EP 175153	B1	19910327		
R: DE, GB				
JP 61050146	A2	19860312	JP 1984-172571	19840820
JP 03076732	B4	19911206		
JP 61050147	A2	19860312	JP 1984-172572	19840820
JP 03076733	B4	19911206		
JP 61072247	A2	19860414	JP 1984-193607	19840914
JP 04002177	B4	19920116		
JP 61072248	A2	19860414	JP 1984-193608	19840914
JP 04002178	B4	19920116		
AU 8546417	A1	19860227	AU 1985-46417	19850819
AU 599573	B2	19900726		
US 5075202	A	19911224	US 1990-581210	19900910
PRIORITY APPLN. INFO.:			JP 1984-172571	19840820
			JP 1984-172572	19840820
			JP 1984-193607	19840914
			JP 1984-193608	19840914
			US 1985-766119	19850815
			US 1987-8141	19870122
			US 1987-142344	19871228
			US 1989-379654	19890711

AB A photog. processing method is described which causes less stains at cut





surfaces of a photog. paper and provides stable dye images. The method involves imagewise exposure of a photosensitive material containing a Ag halide emulsion layer on (1) a support coated with an electron-beam cured resin or (2) one side or both sides of a support of an opaque thermoplastic film comprising a polyester film coated on one or both sides with fine particles of the white pigment and/or a polyester film containing the white particles dispersed in it, color developing, bleach-fixing, and stabilizing without any H₂O washing step. Thus, a paper support was coated on both sides with a composition containing Araldite CY 179 62 4,4-dimethyldiphenyliodonium hexafluoroacetate 3, TiO₂ 35 weight parts, electron-beam irradiated, and on one side coated with a Ag halide emulsion containing a coupler. The element was imagewise exposed, developed for 3 min 15 s in a composition containing K₂CO₃ 30, Na₂SO₃ 2, hydroxyamine sulfate

2.2, KBr 1.2, diethylenetriaminepentaacetic acid 2, NaOH 3.4, N-ethylene-N-β-hydroxyethyl-3-methyl-4-aminoaniline HCl 4.6 g, H₂O to 1 L (pH 10.05) at 37.8°, bleach-fixed for 1 min 30 s using a solution containing EDTA Fe-NH₃ salt 50, diethylenetriaminepentaacetic acid 10 g, 70% ammonium thiosulfate 200, 40% ammonium sulfite 10 mL, H₂O to 1 L (pH 6.8) at 37.8°, stabilized for 2 min 10 s in a solution containing 2-methyl-4-isothiazolin-3-one 0.004, 2-methyl-5-chloro-4-isothiazolin-3-one 0.02, 1-hydroxyethylidene-1,1'-diphosphoric acid 0.01, 2-octyl-4-isothiazolin-3-one 0.03, MgCl₂ 0.17, BiCl₃ 0.14, poly(vinylpyrrolidone) 0.1, nitriloacetic acid 3, 28% aqueous NH₄OH 3 g, H₂O to 1 L (pH 7.1) at 30-34°. The obtained sample was superior to a control (subjected to the processing with H₂O washing in place of stabilization) in edge contamination, in stain in the image parts, and also in dye concentration

IT 1310-73-2, uses and miscellaneous 9003-39-8

RL: USES (Uses)
(color photog. processing compns. containing)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

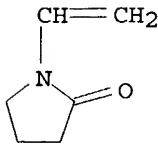
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IC ICM G03C001-80
ICS G03C007-30
CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST color photog processing
IT Polyesters, uses and miscellaneous
RL: USES (Uses)
 (photog. color element with paper support coated with electron beam-curable composition containing, processing method for)
IT Photographic processing
 (color, water washing step elimination in)
IT 67-43-6 139-13-9 584-08-7 869-52-3D, iron complex 1310-73-2
 , uses and miscellaneous 1336-21-6 2682-20-4 2809-21-4 7439-89-6D,
 complex with triethylenetetraminehexaacetic acid 7757-83-7 7758-02-3,
 uses and miscellaneous 7783-18-8 7786-30-3, uses and miscellaneous
 7787-60-2 9003-39-8 10196-04-0 13973-61-0 21265-50-9
 26172-55-4 26530-20-1 103481-24-9 103690-85-3 104002-61-1
RL: USES (Uses)
 (photog. processing compns. containing)
IT 673-48-3 7727-43-7 13048-33-4 13463-67-7, uses and miscellaneous
 15625-89-5 25038-59-9, uses and miscellaneous 25068-38-6 25085-98-7
 61245-67-8
RL: USES (Uses)
 (photog. color element with paper support coated with electron beam-curable composition containing, processing method for)

L32 ANSWER 31 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1986:43180 CAPLUS
DOCUMENT NUMBER: 104:43180
TITLE: Image formation material and correction method
INVENTOR(S): Taguchi, Takao; Kumagai, Koji; Kodaira, Takeo
PATENT ASSIGNEE(S): Toppan Printing Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 60140237	A2	19850725	JP 1983-249735	19831227
JP 2938073	B2	19990823		
PRIORITY APPLN. INFO.:			JP 1983-249735	19831227

AB A material for metal image formation has a flexible support, a thin metal layer, and a photosensitive polymer layer containing a component that changes its solubility and a component that changes its color, both by irradiation
One of

the claimed methods for the correction of insufficient dot area of halftone images or line widths involves total exposure (<15% of the previous exposure) and successive or simultaneous development and etching of the metal thin layer. Another method involves exposure ($\geq 60\%$ of normal exposure) and a 2nd exposure ($\leq 15\%$ of the previous exposure) to parts that need not be corrected, followed by successive or simultaneous development and etching similar to before. These simplify and facilitate free correction of the exposed plate, with the aid of a visible image. Thus, an Al-laminated poly(ethylene terephthalate) film (Metalumy) was coated with a photosensitive composition containing Styrite HS-2 (an alkali-soluble resin) 5, trimethylolpropane triacrylate 5, Michler's ketone 0.5, 2-(o-chlorophenyl)-4,5-diphenylimidazole dimer 1.0, leuco malachite green 0.5, and 2-butanone 90 g and then coated with a poly(vinyl alc.) protective layer. Exposure through an original produced a green image. Immersion in 0.3% aqueous KOH for 10 s, rubbing with a sponge, immersion in an aqueous solution containing HNO₃, CuO and ammonium acid fluoride gave

an Al metal image having a high resolution, a high contrast, and a d. of 4.0.

IT 9003-39-8

RL: USES (Uses)

(correction solns. containing carbon black and, for aluminum metal images using photosensitive polymer compns.)

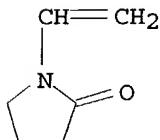
RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX, NAME)

CM 1

CRN 88-12-0

CMF C₆ H₉ N O



IT 1310-58-3, uses and miscellaneous

RL: USES (Uses)

(developer solns. containing, for forming aluminum images on poly(ethylene terephthalate) film supports using photosensitive polymer compns.)

RN 1310-58-3 CAPLUS

CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K- OH

IC ICM G03C005-00
ICS G03C001-00
ICA G03F001-00
CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST image formation metal printing out; photosensitive polymer metal image formation
IT Carbon black, uses and miscellaneous
RL: USES (Uses)
(correction solns. containing poly(vinylpyrrolidone) and, for aluminum metal images using photosensitive polymer compns.)
IT Lithographic plates
Printing plates
(formation and correction of aluminum images with photosensitive polymer compns. in fabrication of)
IT Photoimaging compositions and processes
(photosolubilizable polymer compns. containing leuco dye and, for metal image formation and correction)
IT Rubber, butadiene, uses and miscellaneous
RL: USES (Uses)
(cyclized, photosensitive polymer compns. containing, for aluminum metal image formation and correction)
IT 9003-39-8
RL: USES (Uses)
(correction solns. containing carbon black and, for aluminum metal images using photosensitive polymer compns.)
IT 1310-58-3, uses and miscellaneous
RL: USES (Uses)
(developer solns. containing, for forming aluminum images on poly(ethylene terephthalate) film supports using photosensitive polymer compns.)
IT 1317-38-0, uses and miscellaneous 7697-37-2, uses and miscellaneous
7705-08-0, uses and miscellaneous 12125-01-8
RL: USES (Uses)
(etching solns. containing, for forming aluminum images on poly(ethylene terephthalate) film supports using photosensitive polymer compns.)
IT 7429-90-5P, uses and miscellaneous
RL: PREP (Preparation); USES (Uses)
(images, on poly(ethylene terephthalate) film supports, formation and correction of, photosolubilizable polymer compns. containing leuco dye for)
IT 90-94-8 129-73-7 1592-43-4 6143-80-2 15625-89-5 76283-05-1
RL: USES (Uses)
(photosensitive polymer compns. containing, for aluminum metal image formation and correction)

L32 ANSWER 32 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1985:229491 CAPLUS
DOCUMENT NUMBER: 102:229491
TITLE: High contrast photoresist developer
INVENTOR(S): Lewis, James Marvin; Owens, Austin; Blakeney, Andrew Joseph
PATENT ASSIGNEE(S): Allied Corp., USA

SOURCE: Eur. Pat. Appl., 23 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 129106	A1	19841227	EP 1984-106059	19840528
EP 129106	B1	19880127		
R: DE, FR, GB, IT				
CA 1251350	A1	19890321	CA 1984-455255	19840528
JP 60012547	A2	19850122	JP 1984-125000	19840618
JP 04062576	B4	19921006		
US 4661436	A	19870428	US 1985-767318	19850819

PRIORITY APPLN. INFO.: US 1983-505571 19830617

AB A developer for a pos. diazo photoresist contains an alkali metal hydroxide, H₂O and ≥0.001% of a nonionic fluorocarbon surfactants. Addition of the surfactant results in increased contrast of the developed image. Thus, a Si wafer (dehydrated at 200° and treated with hexamethyldisilazone) was spun coated with a photoresist containing a novolak resist and diazonaphthoquinonesulfonic acid ester, baked at 100° for 3 min. UV imagewise exposed, immersed in a developer containing 0.271N aqueous KOH, and a mixture of surfactants having formula F(CF₂)_n(CH₂CH₂O)_mCH₂CH₂OH (n = 3-6; m > 5-26) 0.016% at 22° for 60 s, and dried. The sensitivity of the resist was 8 mJ/cm² and contrast 12.5 vs. 25 mJ/cm² and 2.2 using surfactants-free control developer.

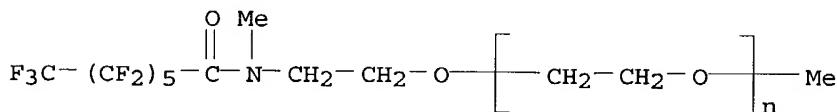
IT 96743-36-1

RL: USES (Uses)

(developer composition containing alkali metal hydroxide and, for pos. diazo photoresists, for increased image contrast)

RN 96743-36-1 CAPLUS

CN Poly(oxy-1,2-ethanediyl), α-methyl-ω-[2-[methyl(2,2,3,3,4,4,5,5,6,6,7,7,7-tridecafluoro-1-oxoheptyl)amino]ethoxy]-(9CI) (CA INDEX NAME)



IT 1310-58-3, uses and miscellaneous 1310-73-2, uses and miscellaneous

RL: USES (Uses)

(developer composition containing nonionic fluorohydrocarbon surfactant and, for

pos. diazo photoresists, for improved image contrast)

RN 1310-58-3 CAPLUS

CN Potassium hydroxide (K(OH)) (9CI) (CA INDEX NAME)

K- OH

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na- OH

IC ICM G03F007-26

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST fluorocarbon surfactant diazo photoresist developer; pos diazo photoresist surfactant developer; nonionic fluorosurfactant photoresist developer

IT Resists

(developer for, consisting of alkali metal hydroxide and nonionic fluorocarbon surfactant)

IT Phenolic resins, uses and miscellaneous

RL: USES (Uses)

(photoresist composition containing diazo compound and, alkaline developer for, containing nonionic fluorocarbon surfactant, for increased image contrast)

IT Surfactants

(nonionic, fluorocarbon, photoresist alkaline developer composition containing, for improved image contrast)

IT Resists

(photo-, pos.-working, diazo, alkaline developer for, containing nonionic fluorocarbon surfactant, for improved image contrast)

IT 96743-36-1 96743-37-2 96743-38-3 96743-39-4

RL: USES (Uses)

(developer composition containing alkali metal hydroxide and, for pos. diazo photoresists, for increased image contrast)

IT 1310-58-3, uses and miscellaneous 1310-73-2, uses and miscellaneous

RL: USES (Uses)

(developer composition containing nonionic fluorohydrocarbon surfactant

and, for

pos. diazo photoresists, for improved image contrast)

IT 20680-48-2D, esters

RL: USES (Uses)

(photoresist containing, developer composition for, containing alkali metal hydroxide and nonionic fluorocarbon surfactant, for improved image contract)

L32 ANSWER 33 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1980:504855 CAPLUS

DOCUMENT NUMBER: 93:104855

TITLE: Colored pH-sensitive films and their uses
INVENTOR(S): Taga, Hideji
PATENT ASSIGNEE(S): Pilot Ink Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 55003956	A2	19800112	JP 1978-77141	19780626
PRIORITY APPLN. INFO.:			JP 1978-77141	19780626

AB A transparent film is coated with a uniform mixture of a compound whose color changes with pH change, a pH controlling agent which controls the pH of the mixture in the range where the compound is in colored state and a hydrophilic solid binder to give a pH-sensitive imaging sheet useful for preparing transparencies for overhead projectors. The transparency can be prepared by drawing images on the film by using a marking pen containing an acidic or alkaline solution depending on the type of the pH-sensitive compound

The

pH-sensitive compound can be selected from various pH indicators whose colored state absorbs light from fluorescent lamps., etc. Thus, a film support was coated with a composition consisting of Bromophenol Blue 0.5, Bromocresol Green 0.5, Gesenol GL-0 2 [a poly(vinyl alc.)] 5.0, Na₂CO₃ 0.5, EtOH 20, and H₂O 73.5 parts to give a blue film. When images are drawn with a solution containing concentrate H₂SO₄ 0.5, ethylene glycol 10, yellow dextrin 3, and H₂O 86.5 parts, fluorescent type yellow images were formed. The images could be easily corrected by using a correction fluid composed of triethanolamine 10, H₂O 89.8, and Adekatol SW (a nonionic surfactant) 0.2 part.

IT 1310-73-2, uses and miscellaneous

RL: USES (Uses)

(inks containing, for drawing or erasing images on pH-sensitive image recording sheet)

RN 1310-73-2 CAPLUS

CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

IT 9003-39-8

RL: USES (Uses)

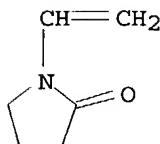
(pH-sensitive imaging sheet containing pH indicator and, for overheat projector transparencies)

RN 9003-39-8 CAPLUS

CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC B41M005-12; C09K009-00; G03C011-22
CC 74-8 (Radiation Chemistry, Photochemistry, and Photographic Processes)
ST pH sensitive imaging film; projection transparency film
IT Projection slides
 (pH-sensitive imaging sheets for, for overhead projectors)
IT 64-17-5, uses and miscellaneous 64-19-7, uses and miscellaneous
77-09-8 102-71-6, uses and miscellaneous 107-21-1, uses and
miscellaneous 111-46-6, uses and miscellaneous 144-62-7, uses and
miscellaneous 497-19-8, uses and miscellaneous 1310-73-2, uses
and miscellaneous 7447-40-7, uses and miscellaneous 7647-01-0, uses
and miscellaneous 7664-93-9, uses and miscellaneous 9004-53-9
9016-45-9 12220-28-9 74434-15-4
RL: USES (Uses)
 (inks containing, for drawing or erasing images on pH-sensitive image
 recording sheet)
IT 76-60-8 115-39-9 6358-69-6 28631-66-5 28983-56-4 74434-60-9
RL: USES (Uses)
 (pH-sensitive imaging sheet containing binder resin and, for overhead
 projector transparencies)
IT 9002-89-5 9003-20-7 9003-39-8
RL: USES (Uses)
 (pH-sensitive imaging sheet containing pH indicator and, for overhead
 projector transparencies)

L32 ANSWER 34 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1978:122164 CAPLUS
DOCUMENT NUMBER: 88:122164
TITLE: Preventing deposition in polymerization and
polymerization reaction apparatus
INVENTOR(S): Cohen, Louis
PATENT ASSIGNEE(S): Goodrich, B. F., Co., USA
SOURCE: Ger. Offen., 46 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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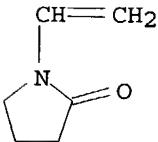
DE	2735770	A1	19780223	DE	1977-2735770	19770809
US	4081248	A	19780328	US	1977-781828	19770328
DK	7703030	A	19780217	DK	1977-3030	19770705
AU	7726824	A1	19790111	AU	1977-26824	19770706
AU	511251	B2	19800807			
SE	7707939	A	19780217	SE	1977-7939	19770707
ZA	7704107	A	19780530	ZA	1977-4107	19770707
CA	1095343	A1	19810210	CA	1977-282654	19770713
NL	7707968	A	19780220	NL	1977-7968	19770718
BR	7704893	A	19780404	BR	1977-4893	19770726
GB	1592403	A	19810708	GB	1977-32497	19770803
JP	53023381	A2	19780303	JP	1977-93479	19770805
FR	2362165	A1	19780317	FR	1977-24965	19770812
NO	7702843	A	19780217	NO	1977-2843	19770815
BE	857827	A1	19771216	BE	1977-180207	19770816
ES	461640	A1	19781201	ES	1977-461640	19770816
PRIORITY APPLN. INFO.:				US	1976-714317	19760816
				US	1977-781828	19770328
AB (I)	An aqueous solution containing NaOH, m-phenylenediamine-resorcinol copolymer [51774-88-0], and a dispersant such as poly(vinyl alc.) (II) [9002-89-5] or hydroxypropyl Me cellulose [9004-65-3] was sprayed on the interior surfaces of a polymerization reactor to minimize PVC [9002-86-2] deposition on the surfaces during the manufacture of PVC by suspension polymerization Thus, an aqueous					
	solution containing I 0.02, II 0.004, NaOH 0.2, and Na ascorbate 0.05% was sprayed on reactor surfaces which were then rinsed with water.					
IT	1310-73-2, uses and miscellaneous 9003-39-8					
	RL: USES (Uses) (antifouling coating compns. containing, for polymerization reactors for vinyl monomers)					
RN	1310-73-2 CAPLUS					
CN	Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)					

Na—OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1 ,

CRN 88-12-0
CMF C6 H9 N O



IC C08F002-00
CC 36-3 (Plastics Manufacture and Processing)
ST PVC manuf nonfouling; phenylenediamine resorcinol copolymer antifouling
IT Fouling
(prevention of, of reactors for polymerization of vinyl monomers)
IT Polymerization
(suspension, of vinyl chloride, antifouling coatings for reactors in)
IT 1310-73-2, uses and miscellaneous 9002-89-5 9003-39-8
9004-65-3 51774-88-0
RL: USES (Uses)
(antifouling coating compns. containing, for polymerization
reactors for vinyl monomers)
IT 9002-86-2P
RL: PREP (Preparation)
(manufacture of suspension, antifouling coatings for reactors in)

L32 ANSWER 35 OF 35 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1976:24447 CAPLUS
DOCUMENT NUMBER: 84:24447
TITLE: Visual recording
INVENTOR(S): Watanabe, Akio; Murata, Yasuzo
PATENT ASSIGNEE(S): Pilot Pen Co., Ltd., Japan
SOURCE: U.S., 5 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 3870435	A	19750311	US 1972-290353	19720919
PRIORITY APPLN. INFO.:			JP 1969-54399	19690709
			US 1970-53054	19700707

AB The poor handling properties of the ink used in pen-writing type recording in measuring instruments are overcome with the use of an ink containing a colorless or light-colored color coupler in conjunction with a recording sheet a mineral acid 1, an developwr which reacts with the coupler to form visual record of vivid color and highly durable nature. Thus, an aqueous ink containing V2O5 9, NaOH 6, a a Na alkynaphthalenesulfonate 1, poly(vinylpyrrolidone) 20, and water 964 g was used in combination with a recording paper coated by a composition containing lauryl gallate 1, vinyl resin a mineral acid 1, an 1, organic acid 2, silicic acid fine powder 3, and EtOAc 10 g to provide a visual jet-black recording

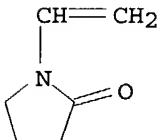
without interrupted ink inscription or ink blotches.
IT 1310-73-2, uses and miscellaneous 9003-39-8
RL: USES (Uses)
(ink containing vanadium pentoxide and, for instrument pen-type recording)
RN 1310-73-2 CAPLUS
CN Sodium hydroxide (Na(OH)) (9CI) (CA INDEX NAME)

Na—OH

RN 9003-39-8 CAPLUS
CN 2-Pyrrolidinone, 1-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 88-12-0
CMF C6 H9 N O



IC B41C
NCL 117036200
CC 74-8 (Radiation Chemistry, Photochemistry, and Photographic Processes)
Section cross-reference(s): 42
ST recording paper instrument ink
IT Copying paper
(for instrument pen-type recording, containing color developer)
IT Inks
(for instrument recording, containing color coupler)
IT Recording
(pen-writing, instrument, ink-paper combination for)
IT Naphthalenesulfonic acid, sodium salt, alkyl derivs.
RL: USES (Uses)
(ink containing vanadium pentoxide and, for instrument pen-type recording)
IT 56-81-5, uses and miscellaneous 9004-53-9
RL: USES (Uses)
(ink containing ammonium metavanadates and, for instrument pen-type recording)
IT 1310-73-2, uses and miscellaneous 9003-39-8
RL: USES (Uses)
(ink containing vanadium pentoxide and, for instrument pen-type recording)
IT 1314-62-1, uses and miscellaneous 7803-55-6
RL: USES (Uses)
(ink containing, as color coupler, for instrument pen-type recording)
IT 67-56-1, uses and miscellaneous 78-93-3, uses and miscellaneous

87-18-3 141-78-6, uses and miscellaneous 1166-52-5 1343-98-2
9011-13-6 25322-68-3 57683-21-3
RL: USES (Uses)
(recording paper coating composition containing,
instruments, for color coupler-containing ink)

=> td que

11365 TD
3401 TDS
14590 TD
(TD OR TDS)
595 QUE
9 QUES
604 QUE
(QUE OR QUES)
L33 0 TD QUE
(TD (W) QUE)

=> d cost

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
CONNECT CHARGES	1.14	43.04
NETWORK CHARGES	0.18	5.88
SEARCH CHARGES	3.64	314.65
DISPLAY CHARGES	188.30	402.77
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CAPLUS FEE (5%)	193.26	766.34
	9.65	23.06
FULL ESTIMATED COST	202.91	789.40
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	-25.73	-49.99

IN FILE 'CAPLUS' AT 16:43:00 ON 12 JUL 2004

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